



Upgrade of the ALICE Inner Tracking System

L. Musa - CERN

*LHeC Workshop
25 June, 2015*

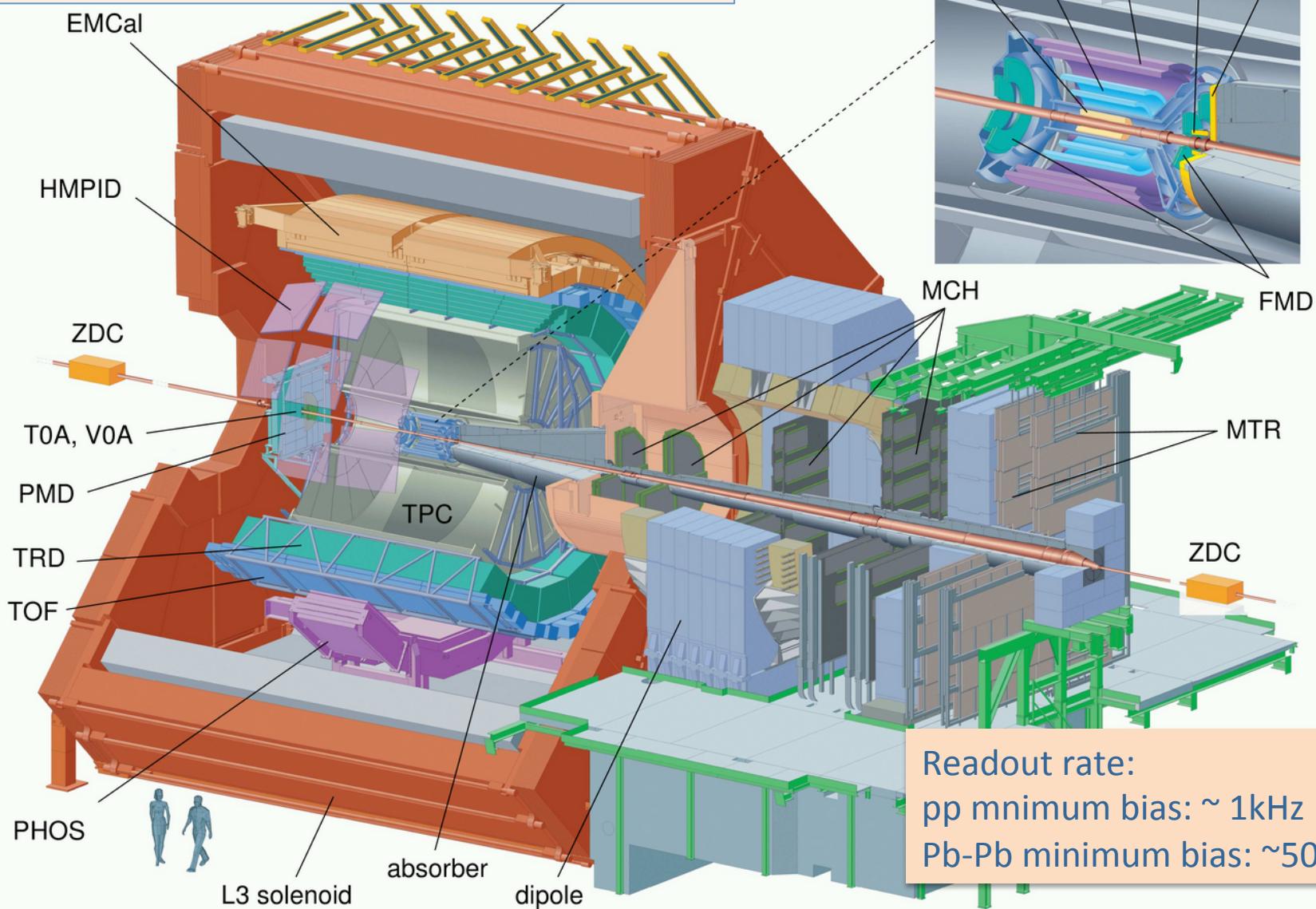
Upgrade of the ALICE Inner Tracking System

OUTLINE

- ALICE current set-up and Inner Tracking System
- Upgrade motivations and strategy
- Upgrade design objectives
- Layout and main components
- Detector simulated performance

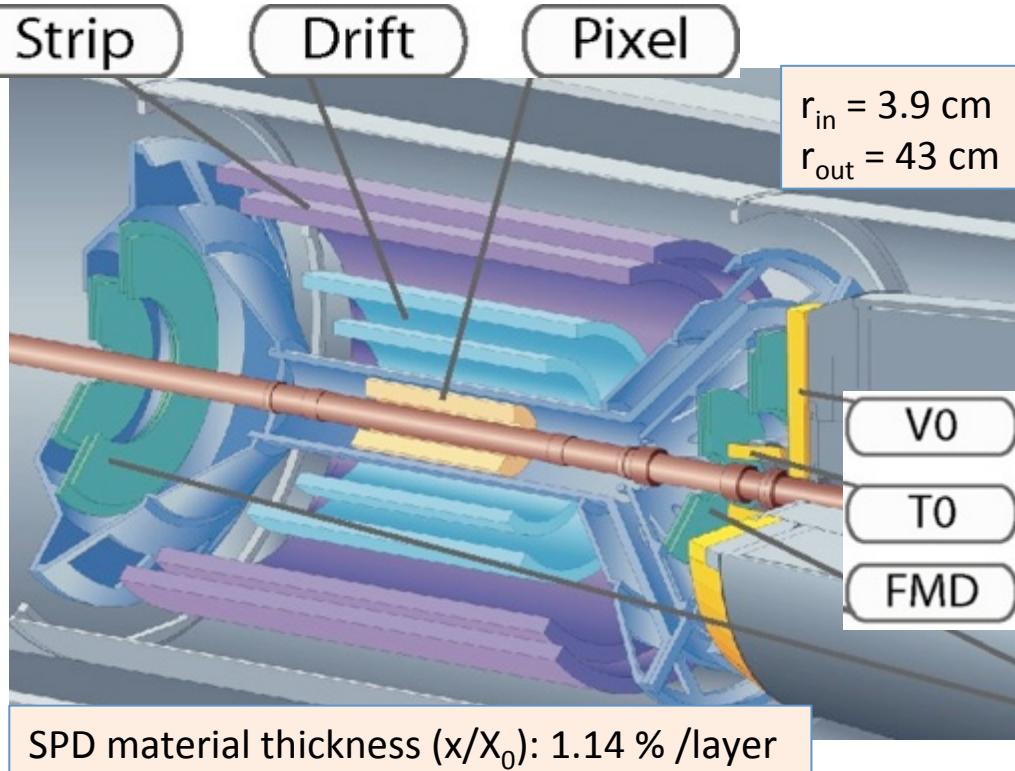
The Current ALICE Detector

Only LHC experiment dedicated to HI collisions



Readout rate:
pp minimum bias: ~ 1kHz
Pb-Pb minimum bias: ~500 Hz

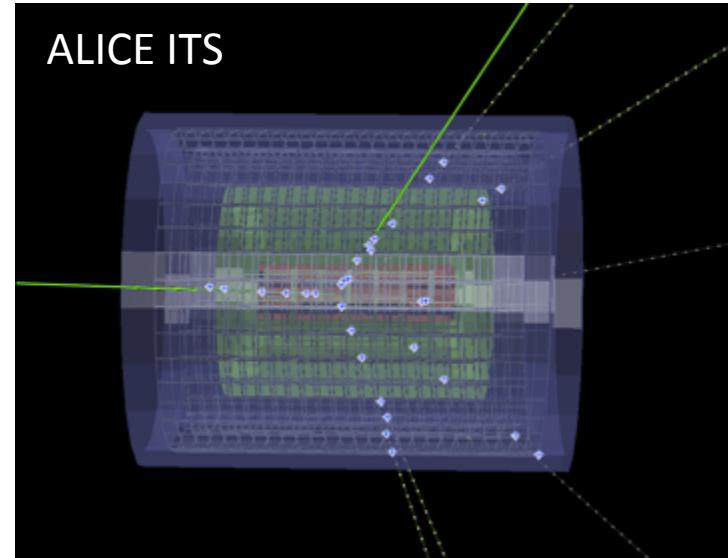
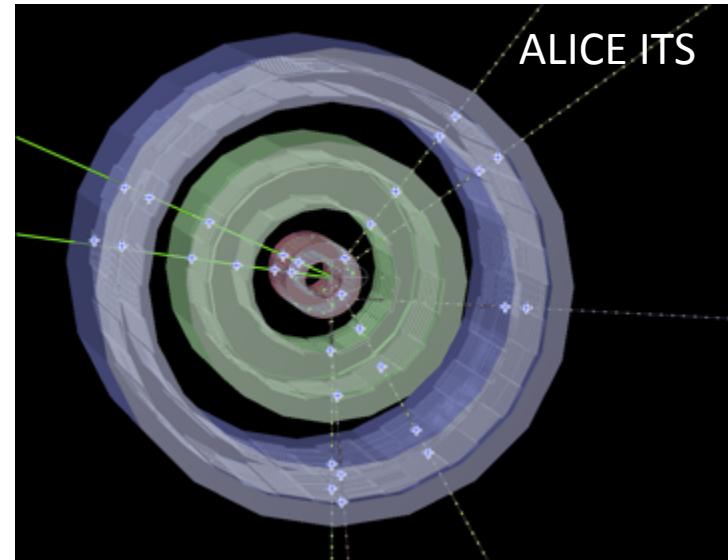
The Current ALICE Inner Tracking System



Current ITS

6 concentric barrels, 3 different technologies

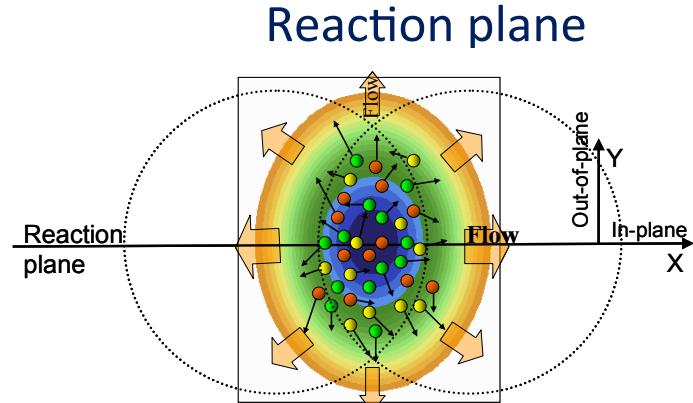
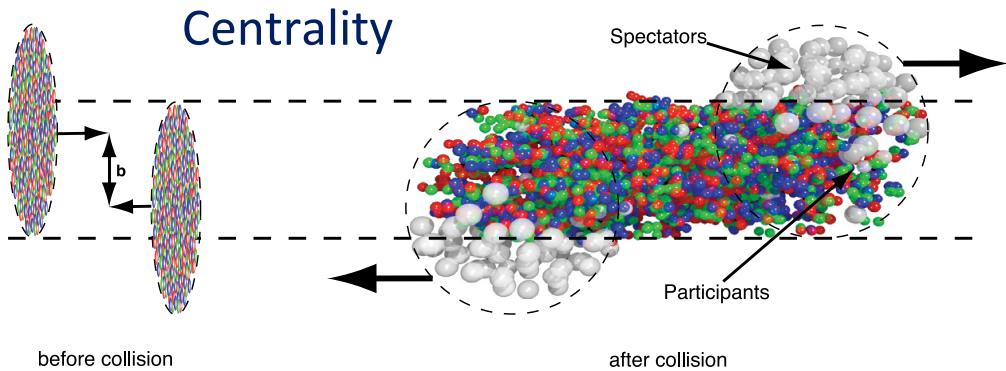
- 2 layers of silicon pixel (SPD)
- 2 layers of silicon drift (SDD)
- 2 layers of silicon strips (SSD)



ALICE Upgrade: study QGP properties

Progress on the characterization of QGP properties

- precision measurements of **rare probes**
- over a large kinematic range (from high to very low transverse momenta)
- and as function of multi-differential observables: centrality, reaction plane, ...



One example:

precision measurements of spectra, correlations and flow of heavy flavour hadrons at low transverse momenta (**not possible to trigger!!**)

This requires statistics (luminosity) and precision measurements

Target for **upgrade programme** (Run3 + Run4)

- Pb-Pb recorded luminosity $\geq 10 \text{ nb}^{-1}$ $\rightarrow 8 \times 10^{10}$ events

I. Upgrade detectors, readout systems and online systems to

- read out all Pb-Pb interactions at a maximum rate of 50kHz (i.e. $L = 6 \times 10^{27} \text{ cm}^{-2}\text{s}^{-1}$), with a minimum bias trigger (at present 500Hz)
→ Gain a factor **100** in statistics over originally approved programme (Run1 + Run2)

II. Significant improvement of vertexing and tracking capabilities at low p_T

- **New Inner tracking System**

It targets LHC 2nd Long Shutdown (2018/19)



ALICE Upgrade LoI
September 2012

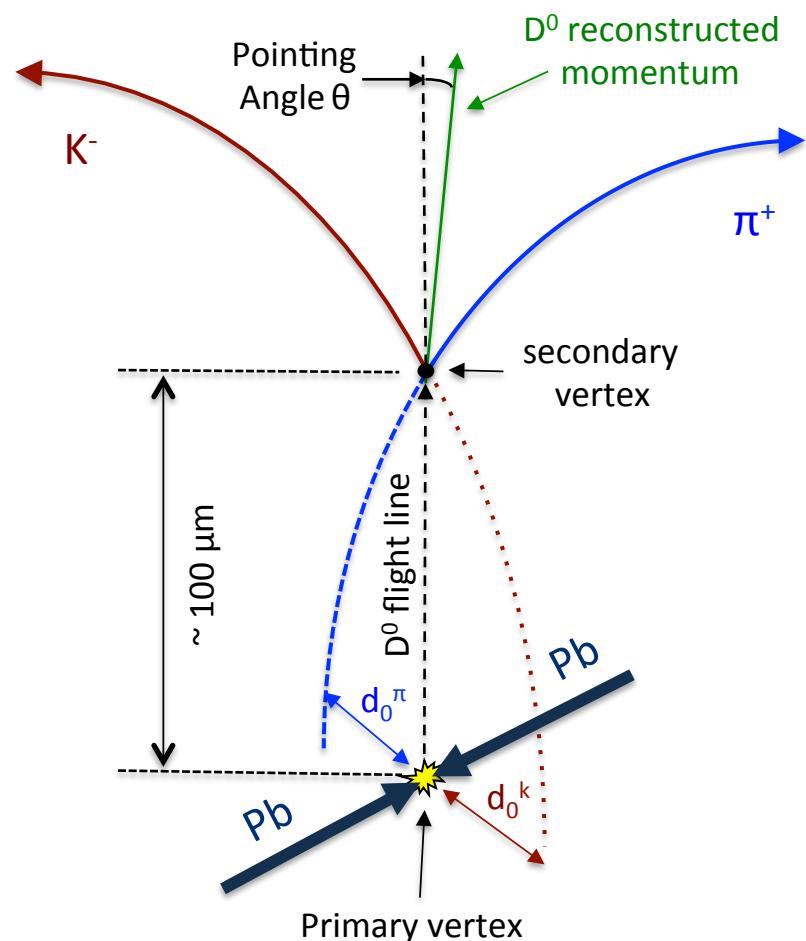


Addendum
September 2013

ITS – Secondary vertex determination

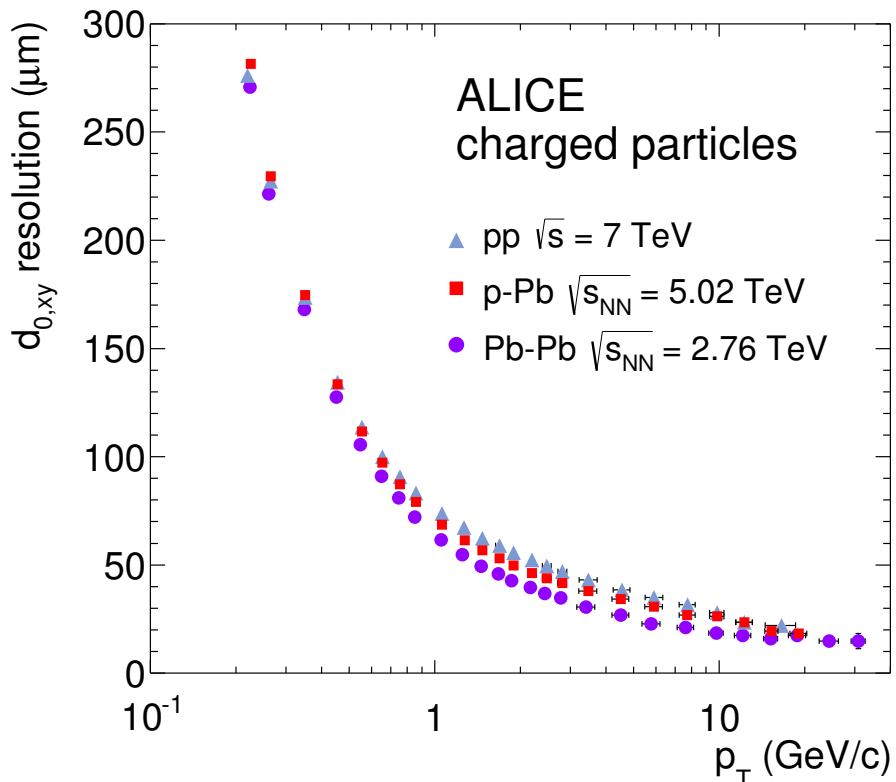


Example: D⁰ meson



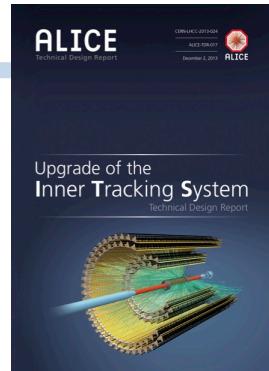
Analysis based on decay topology and invariant mass technique

Very weak dependence on the colliding system



ALICE, Int. J. Mod. Phys. A29 (2014) 1430044

ITS upgrade design objectives



CERN-LHCC-2013-24

1. Improve impact parameter resolution by a factor of ~ 3

- Get closer to IP (position of first layer): 39mm \rightarrow 23mm
- Reduce x/X_0 /layer: $\sim 1.14\%$ $\rightarrow \sim 0.3\%$ (for inner layers)
- Reduce pixel size: currently $50\mu\text{m} \times 425\mu\text{m}$ $\rightarrow O(30\mu\text{m} \times 30\mu\text{m})$

2. Improve tracking efficiency and p_T resolution at low p_T

- Increase granularity:
 - 6 layers \rightarrow 7 layers
 - silicon drift and strips \rightarrow pixels

3. Fast readout

- readout Pb-Pb interactions at > 100 kHz and pp interactions at \sim several 10^5 Hz (currently limited at 1kHz with full ITS)

J. Phys. G (41) 087002

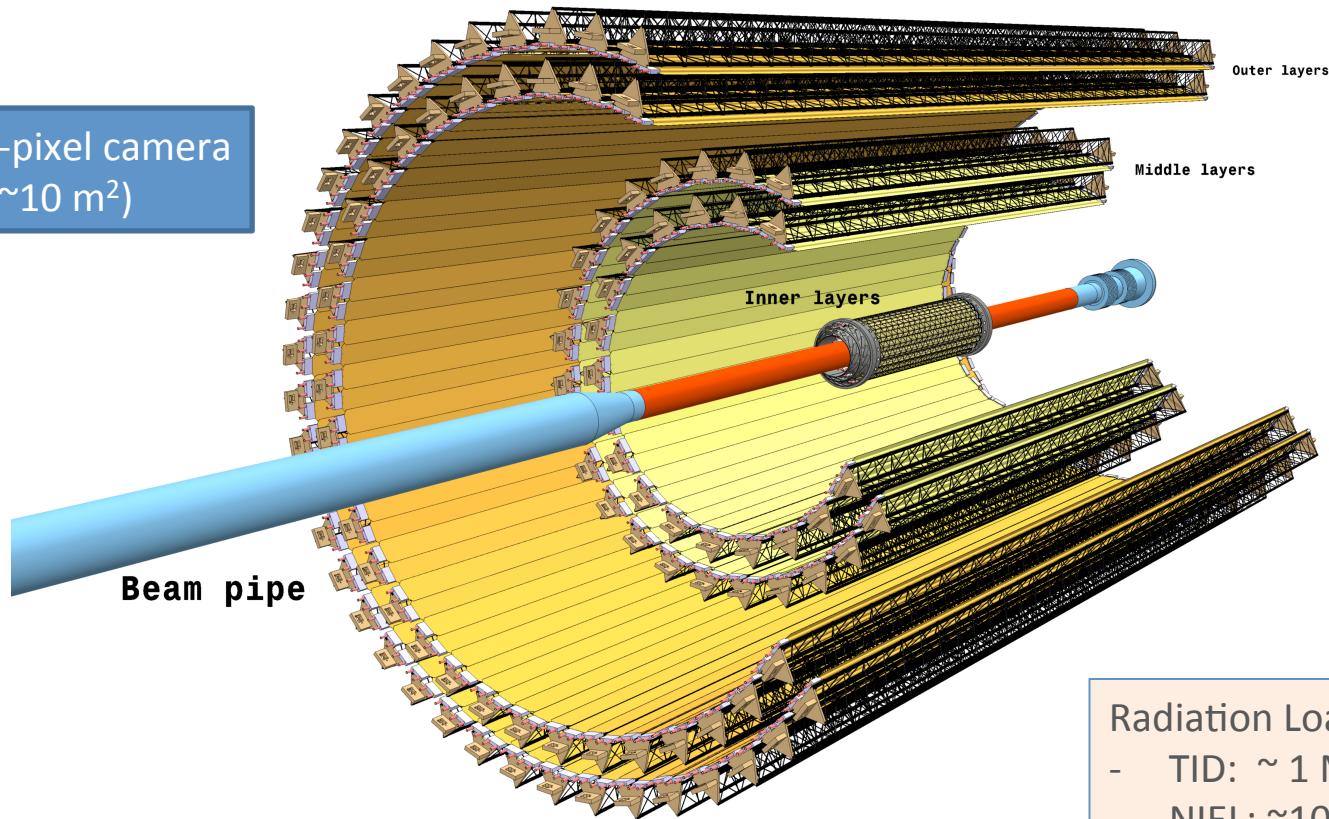
4. Fast insertion/removal for yearly maintenance

- possibility to replace non functioning detector modules during yearly shutdown

Install detector during LHCC LS2 (2018-19)

New ITS Layout

12.5 G-pixel camera
(~10 m²)



7-layer barrel geometry based on MAPS

r coverage: 23 – 400 mm

η coverage: $|\eta| \leq 1.22$
for tracks from 90% most luminous region

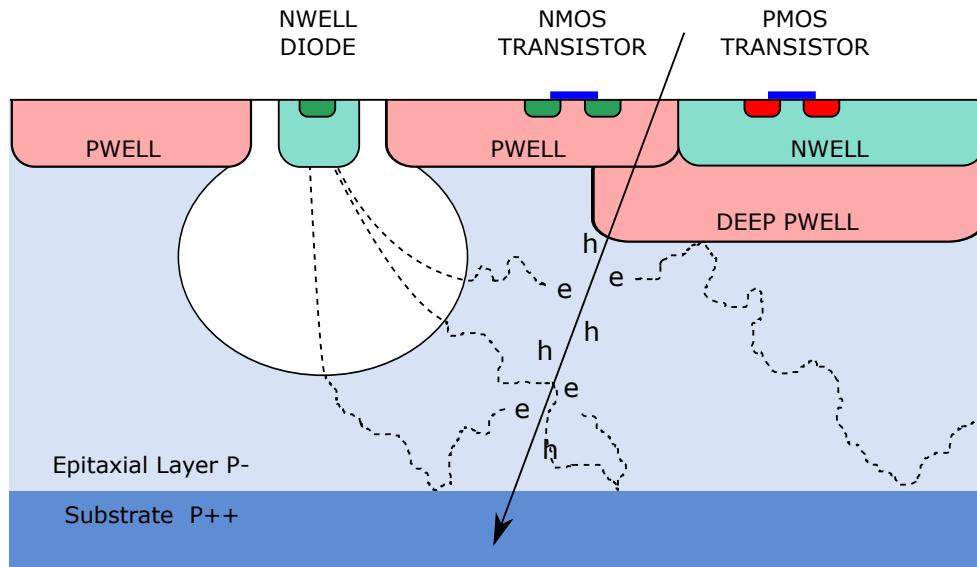
3 Inner Barrel layers (**IB**)

4 Outer Barrel layers (**OB**)

Material /layer : 0.3% X₀ (IB), 1% X₀ (OB)

ITS Pixel Chip – technology choice

CMOS Pixel Sensor using TowerJazz 0.18μm CMOS Imaging Process

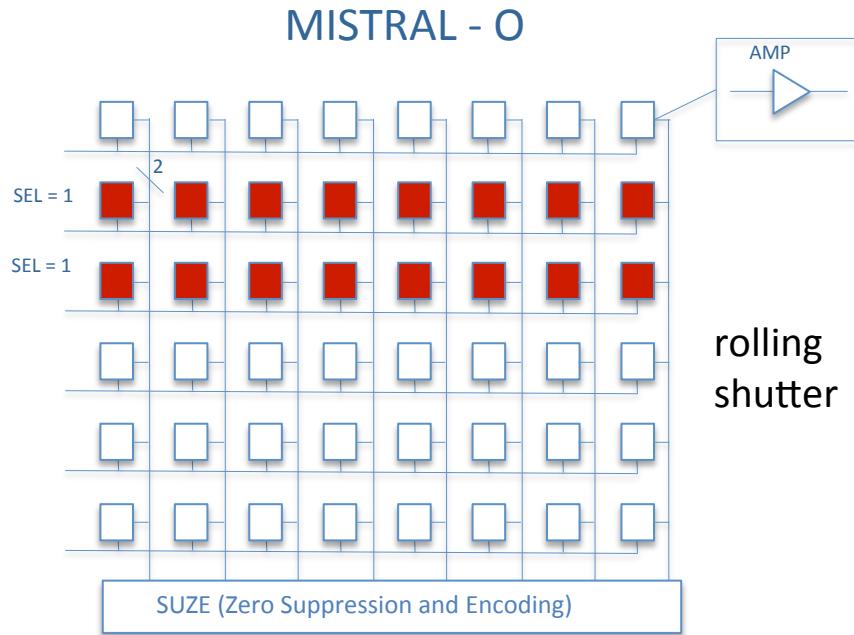
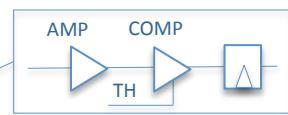
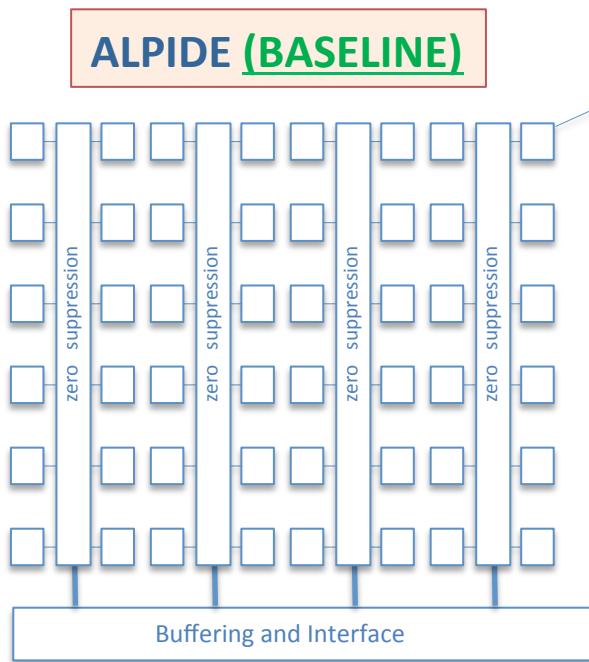


Tower Jazz 0.18 μm CMOS

- feature size 180 nm
- metal layers 6
- ➔ Suited for high-density, low-power
- Gate oxide 3nm
- ➔ Circuit rad-tolerant

- ▶ High-resistivity ($> 1\text{k}\Omega \text{ cm}$) p-type epitaxial layer (20 μm - 40 μm thick) on p-type substrate
- ▶ Small n-well diode (2-3 μm diameter), ~ 100 times smaller than pixel => low capacitance
- ▶ Application of (moderate) reverse bias voltage to substrate can be used to increase depletion zone around NWELL collection diode
- ▶ Quadruple well process: deep PWELL shields NWELL of PMOS transistors, allowing for full CMOS circuitry within active area

ITS Pixel Chip – two architectures



Pixel pitch	$28\mu\text{m} \times 28\mu\text{m}$
Event time resolution	$<2\mu\text{s}$
Power consumption	39mW/cm^2
Dead area	1.1 mm x 30mm

Pixel pitch	$36\mu\text{m} \times 64\mu\text{m}$
Event time resolution	$\sim 20\mu\text{s}$
Power consumption ^(*)	97mW/cm^2
Dead area	1.7 mm x 30mm

ALPIDE and MISTRAL-O have same dimensions (15mm x 30mm), identical physical and electrical interfaces: position of interface pads, electrical signaling, protocol

(*) might further reduce to 73mW/cm^2

pALPIDE-1 (May 2014) – first full-scale prototype

ALPIDE Full Scale prototype

- Dimensions: 30mm x 15 mm
- Pixel Matrix: 1024 cols x 512 rows
- Final pixel pitch: 28 μ m x 28 μ m
- Power consumption: < 40mW/cm²
- Interface pads over matrix
- 1 register/pixel, no final interface

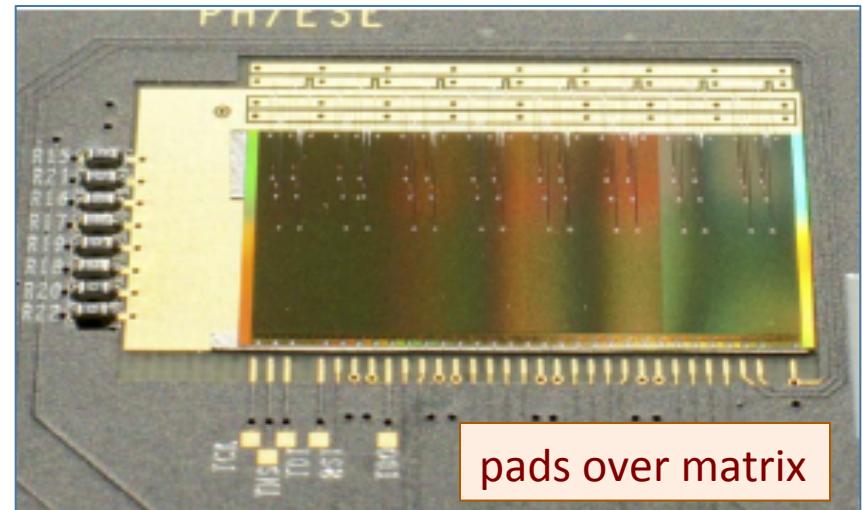
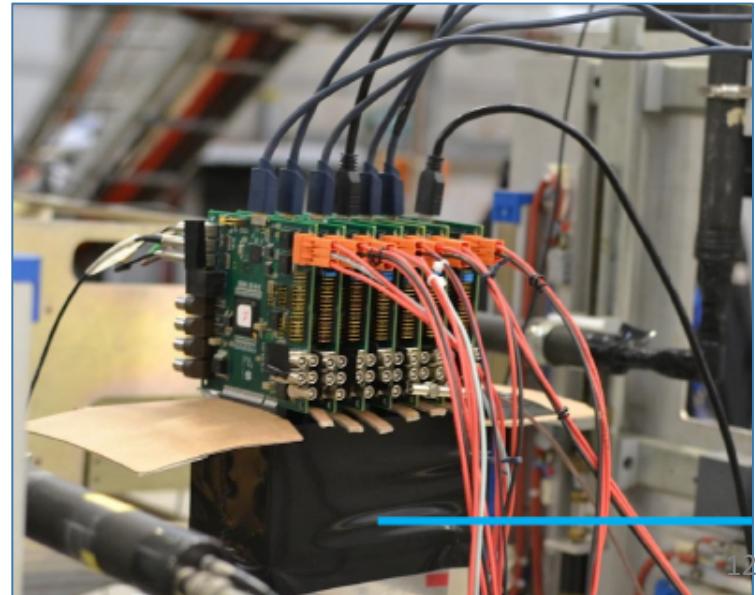
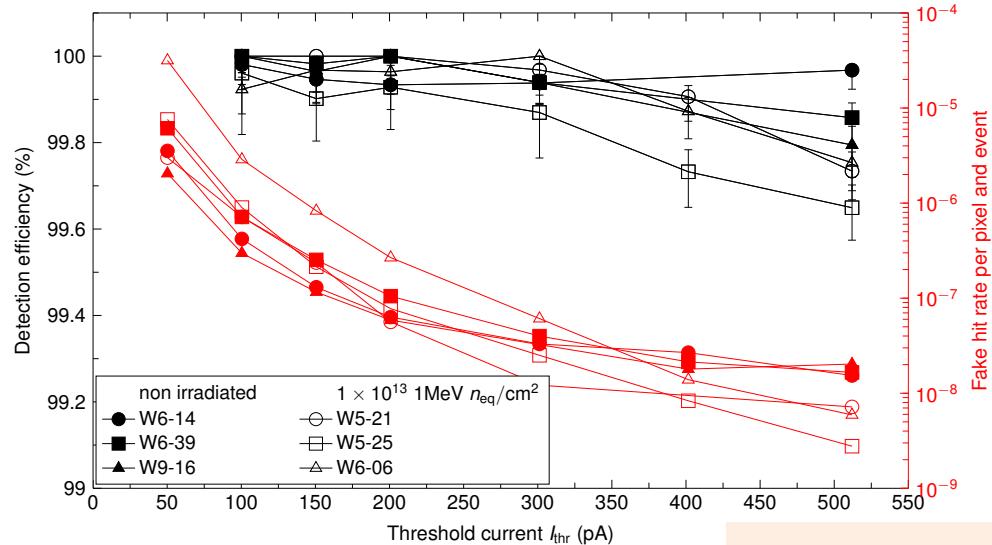


Figure: picture of pALPIDE-1

7-plane telescope based on pALPIDE-1 chip

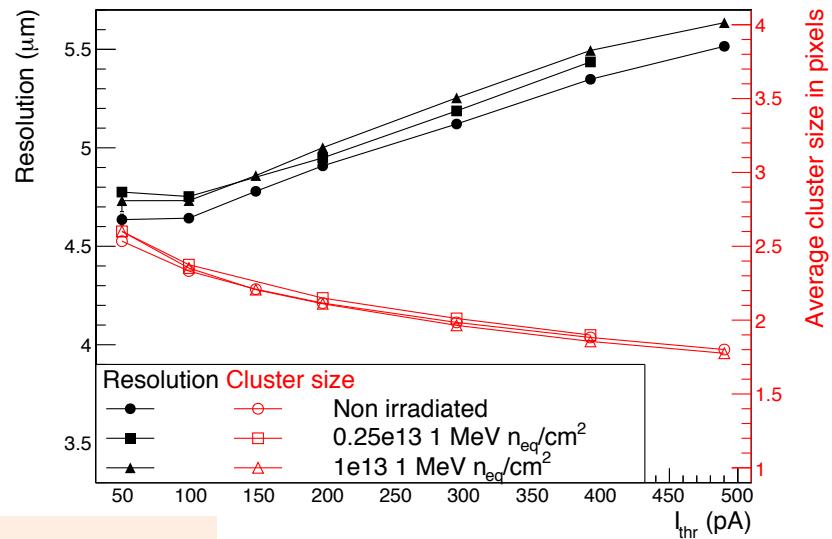


Efficiency and fake hit rate



50 pA ~ 80 e, 500 pA ~ 180 e

Spatial resolution



CERN PS: 5 – 7 GeV π^- (Dec 2014)

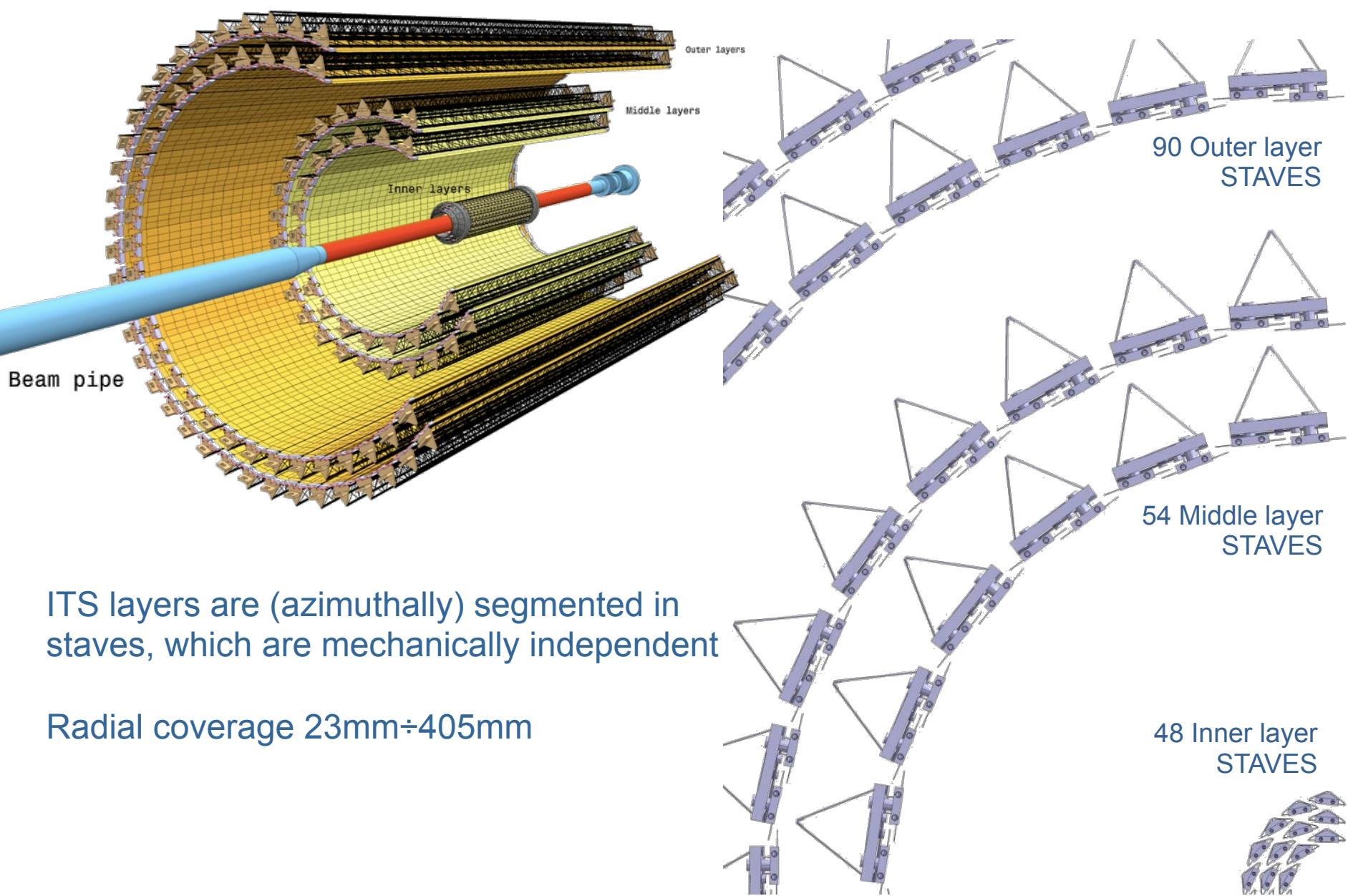
- Results refer to 50 μm thick chips:
 - 3 non irradiated and
 - 3 irradiated with $10^{13} \text{ 1MeV } n_{eq} / \text{cm}^2$

- CERN PS: 5 – 7 GeV π^- (Sep 2014)
- Results refer to 50 μm thick chips:
 - non irradiated
 - irradiated with $0.25 \times 10^{13} \text{ n / cm}^2$
 - irradiated with 10^{13} n / cm^2

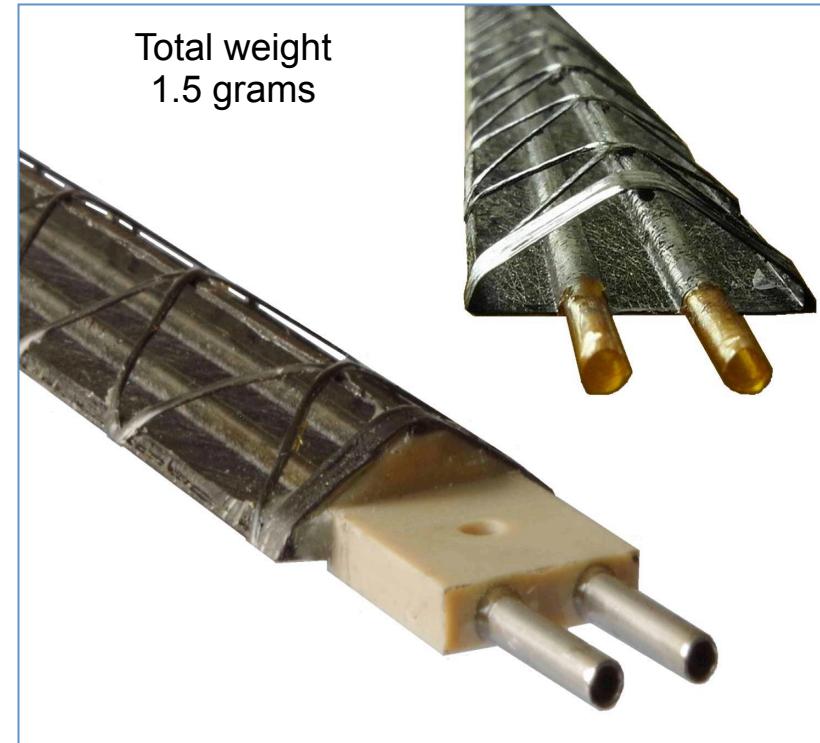
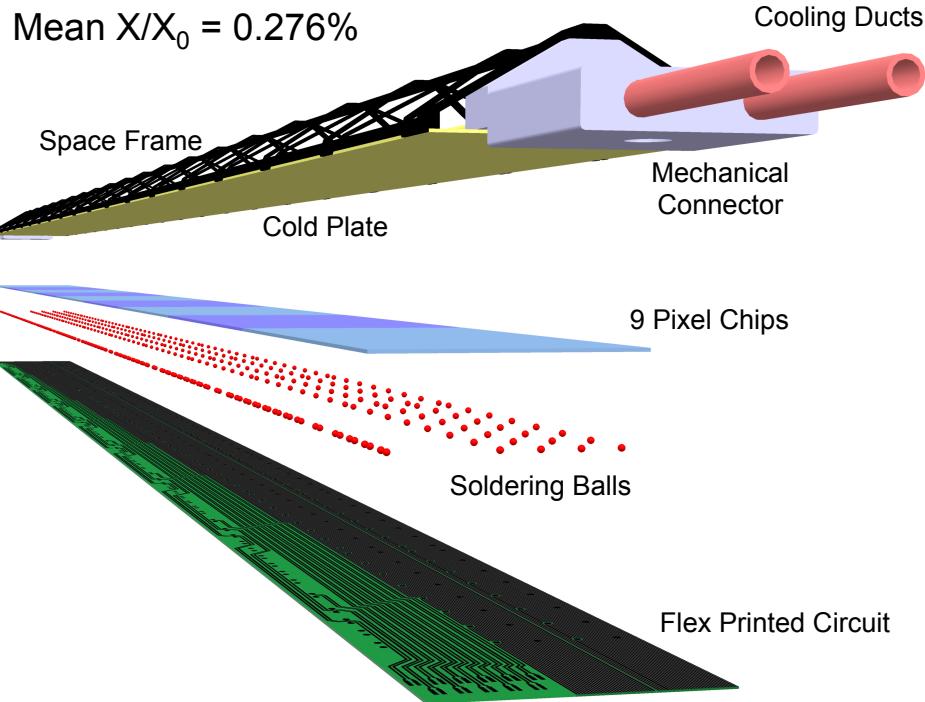
$\lambda_{fake} << 10^{-5} / \text{event/pixel} @ \epsilon_{det} > 99\%$ \rightarrow very large margin over design requirements

$\sigma_{det} \sim 5 \mu\text{m}$ \rightarrow large margin of operation

New ITS layout



New ITS Layout - Inner Barrel Stave



$\langle \text{Radius} \rangle$ (mm): 23,31,39

Nr. of staves: 12, 16, 20

Nr. of chips/layer: 108, 144, 180

Power density: < 100 mW/cm²

Length in z (mm): 290

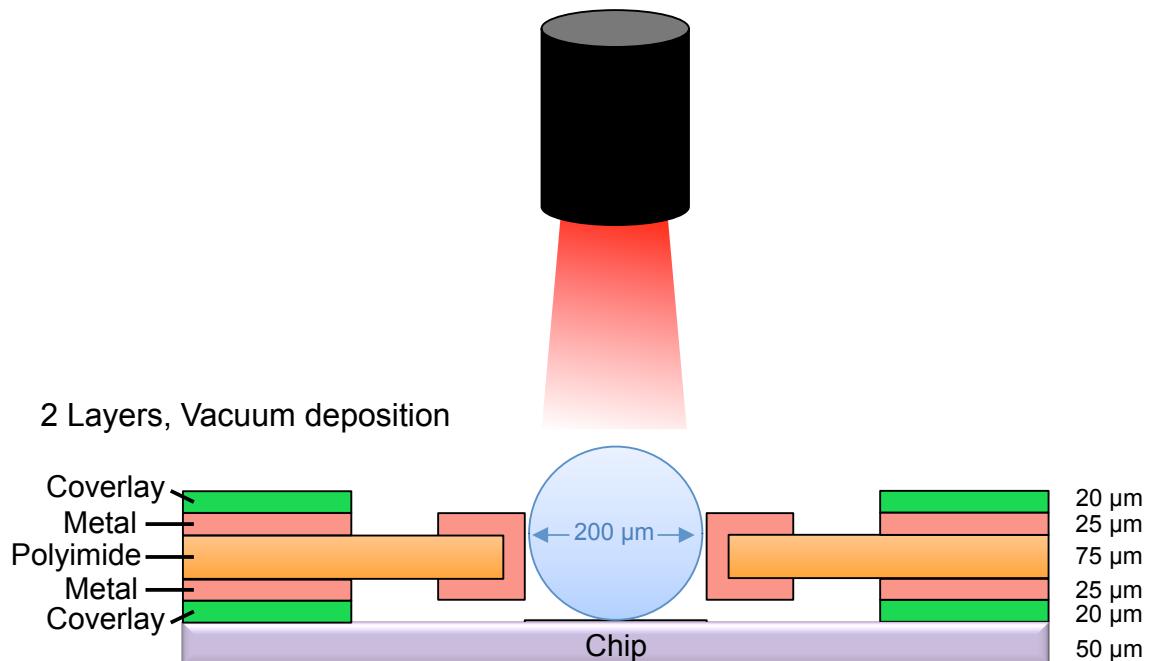
Nr. of chips/stave: 9

Material thickness: ~ 0.3% X_0

Throughput (@100kHz): < 80 Mb/s × cm⁻²

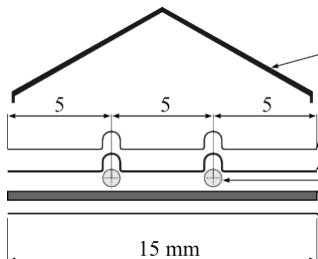
Interconnection of pixel chip to flex PCB

Laser soldering: Interconnection of Pixel chip on flexible printed circuit



Inner Barrel Stave - thermal test

Transversal section:



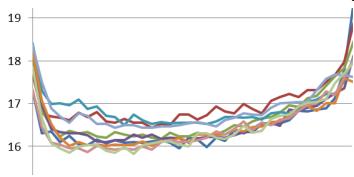
$P_{in} = 1 \text{ bar}$
 $T_{in} = 15.8^\circ \text{C}$
 $Q = 3 \text{ L/h}$
 $T_{out} = 16.6^\circ \text{C}$
 $P_{out} = 0.7 \text{ bar}$



Heating is provided by dummy metalized chip : thickness= 50 μm chip + 20/200 nm Titanium /Platinum

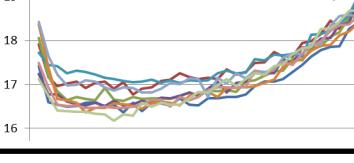
Nominal

Periphery: 0.145 W/chip
 Pixels: 0.03 W/chip



50% safety factor

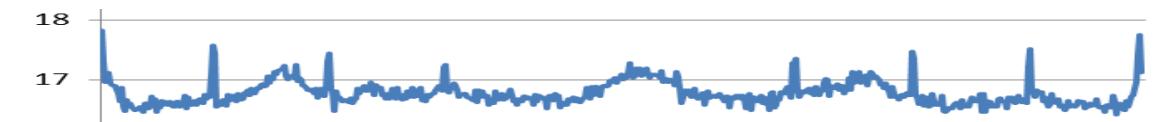
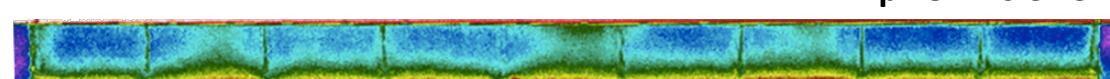
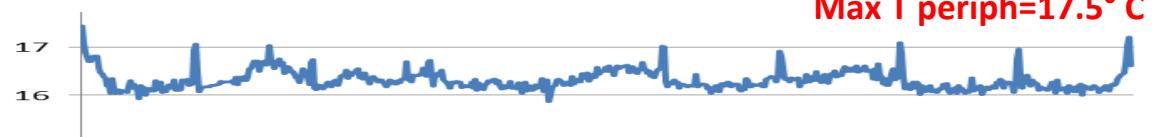
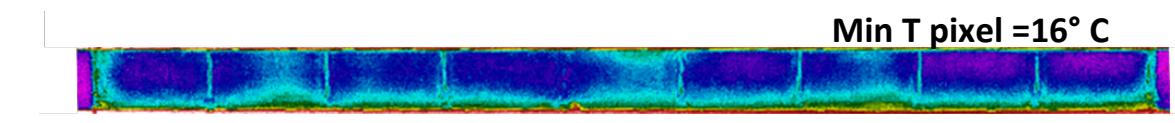
Periphery: 0.217 W/chip
 Pixels: 0.045 W/chip



status

verification of thermal behaviour with

- non uniform power dissipation
- uniform layer of glue



ongoing

verification of thermal behaviour with

- non uniform power dissipation
- no glue at the periphery (2mm) of the chip

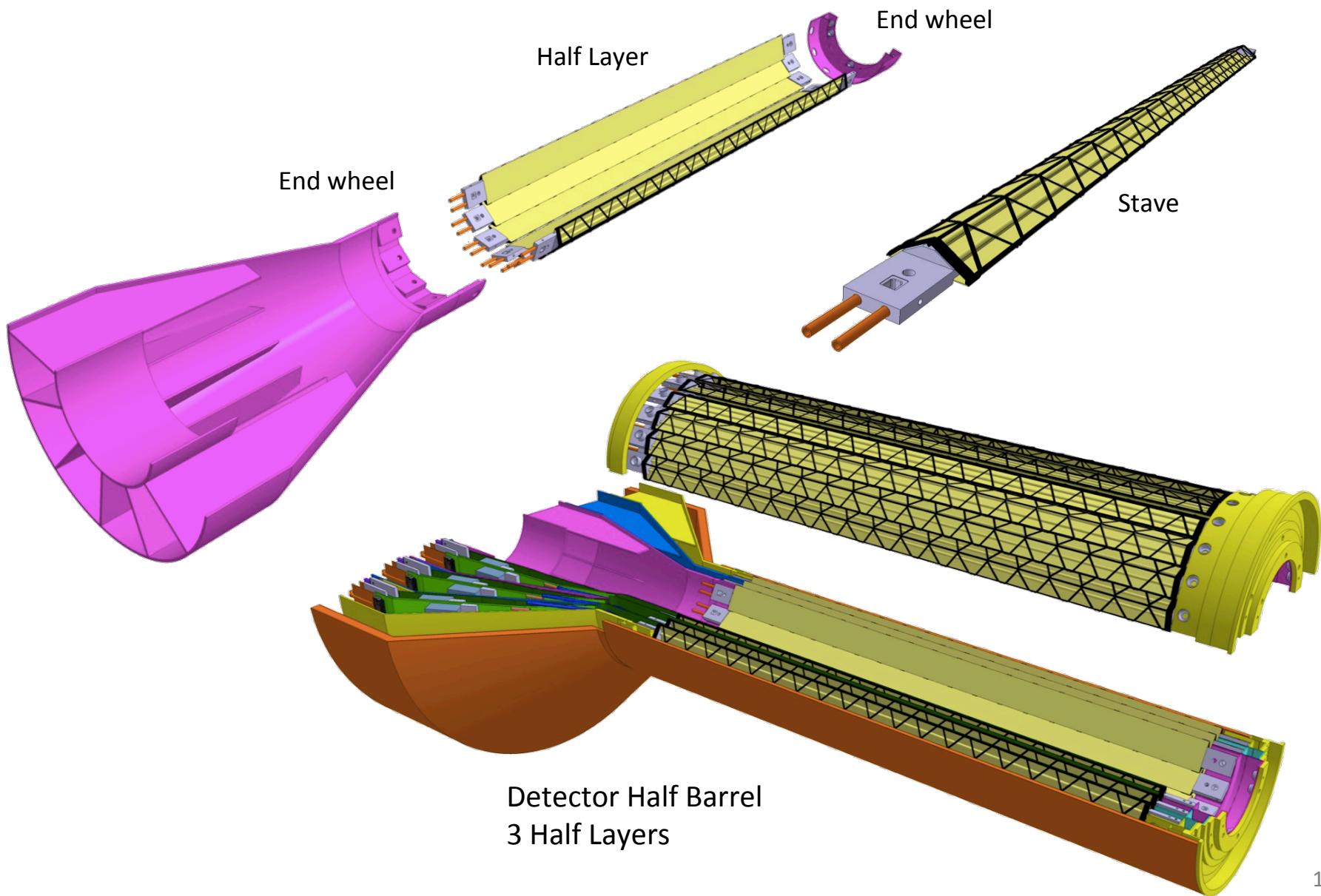
no glue



glue

no glue

Inner Barrel



Inner Barrel – full-scale prototype

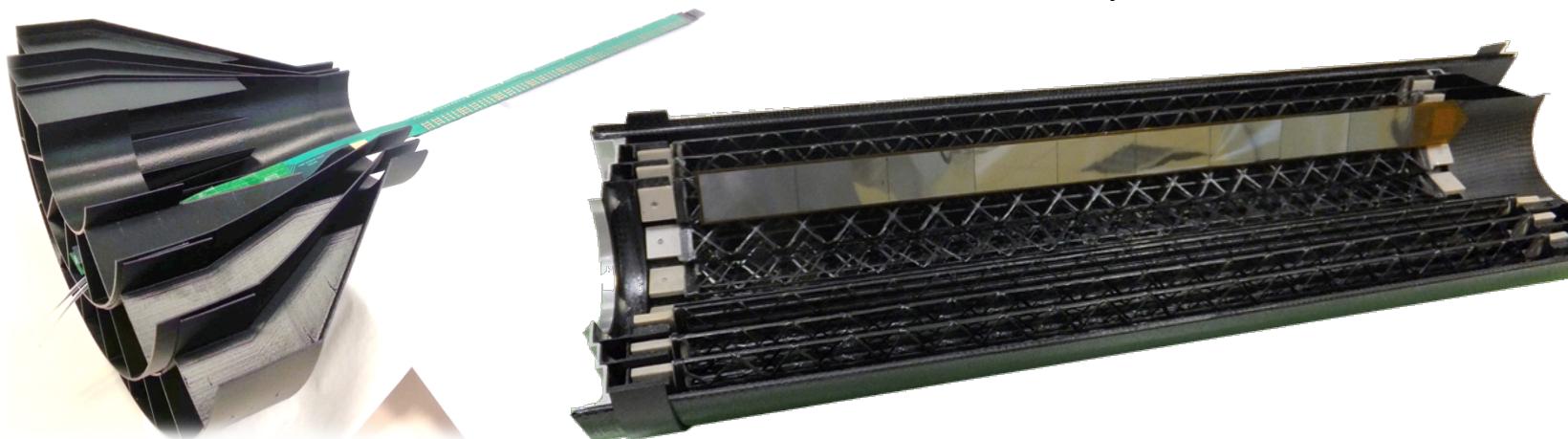
Structural Sandwich

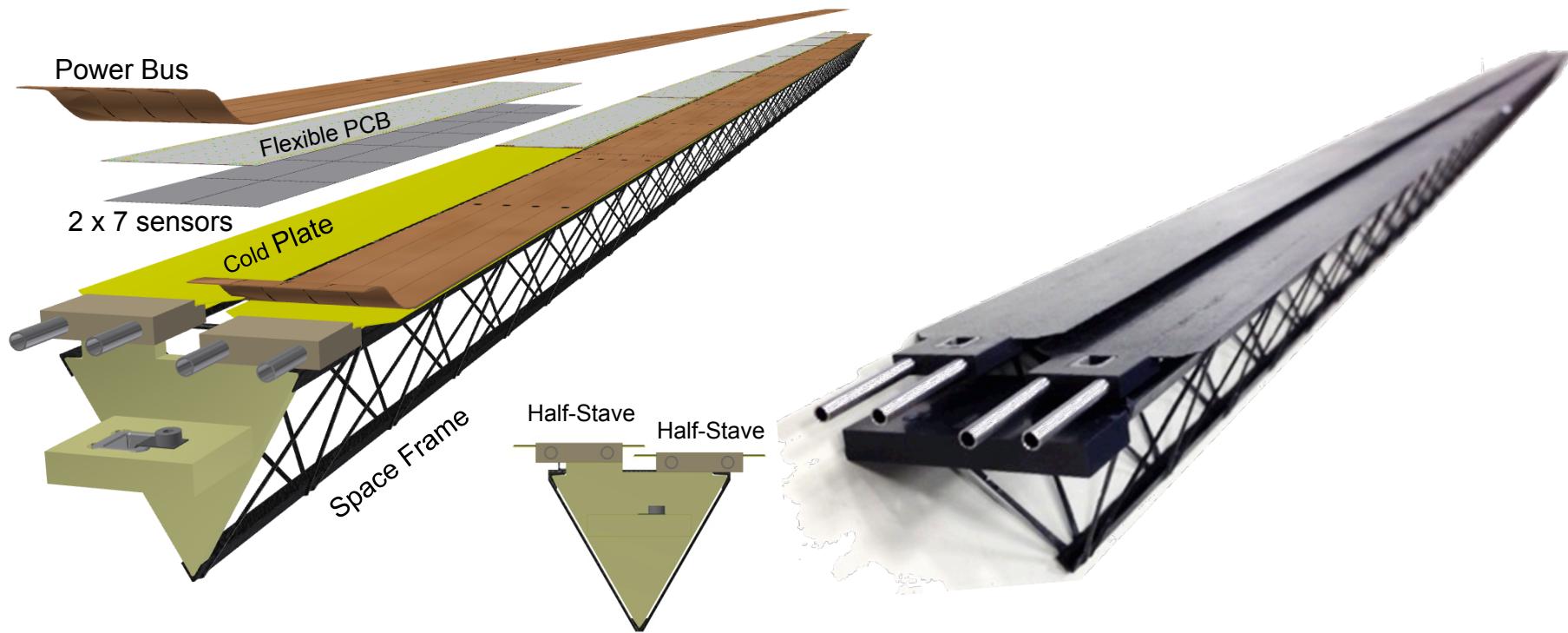


Prototype

Layer 1

Layer 2





Outer Barrel (OB)

<radius> (mm): 194, 247, 353, 405

Nr. staves: 24, 30, 42, 48

Nr. Chips/layer: 6048 (ML), 17740(OL)

Power density < 100 mW / cm²

Length (mm): 900 (ML), 1500 (OL)

Nr. modules/stave: 4 (ML), 7 (OL)

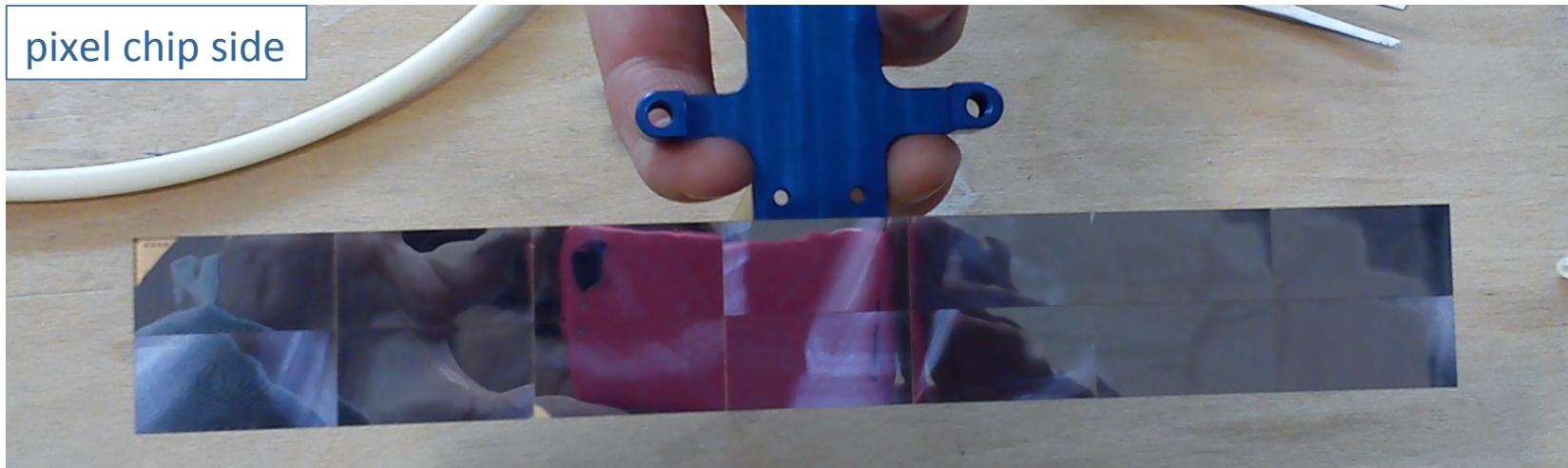
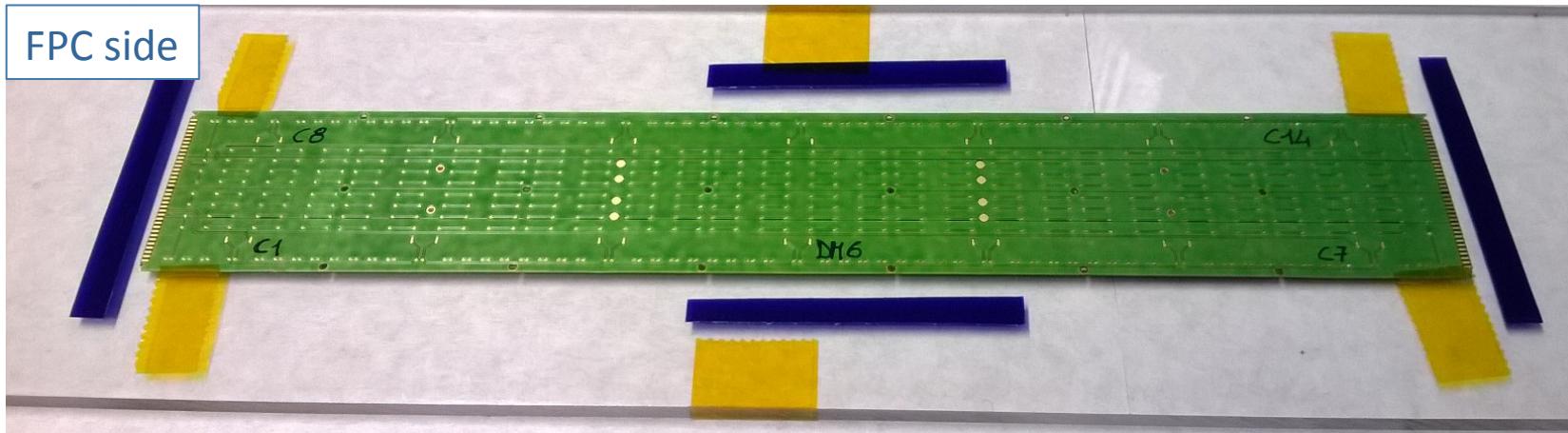
Material thickness: ~ 1% X_0

Throughput (@100kHz): < 3Mb/s × cm⁻²

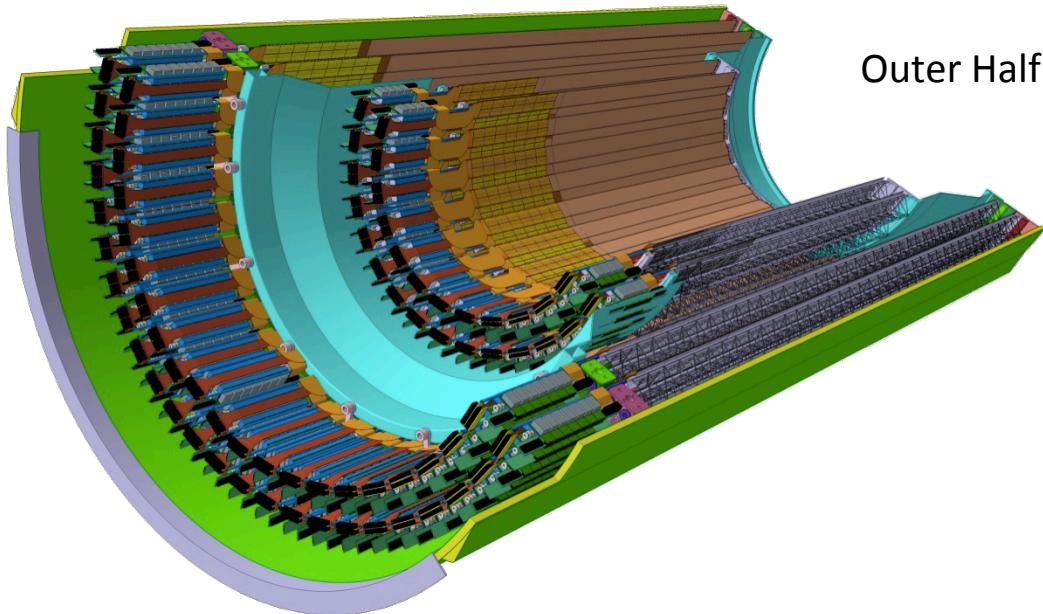
ITS Outer Barrel

HIC: Interconnection of pixel chip on flexible printed circuit (FPC)

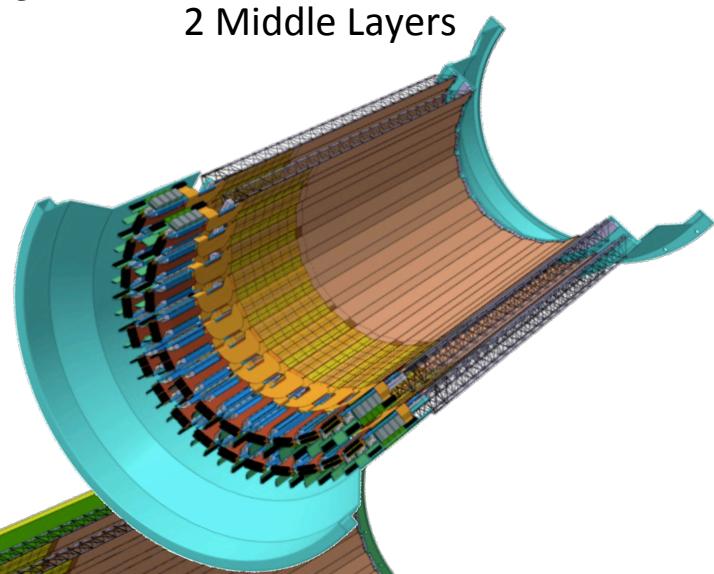
Bari



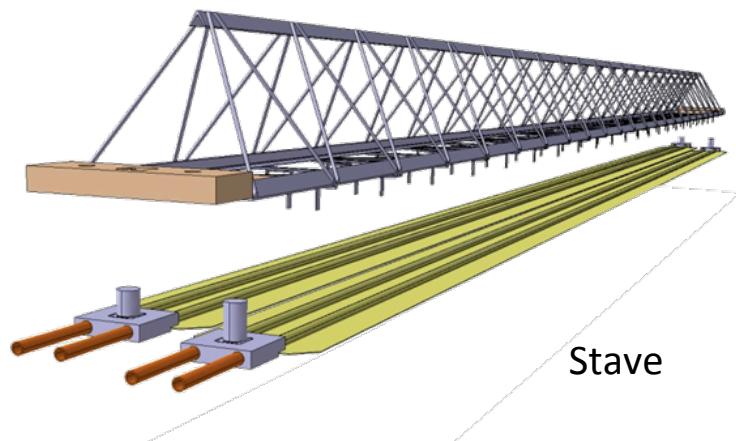
ITS Outer Detector Barrel



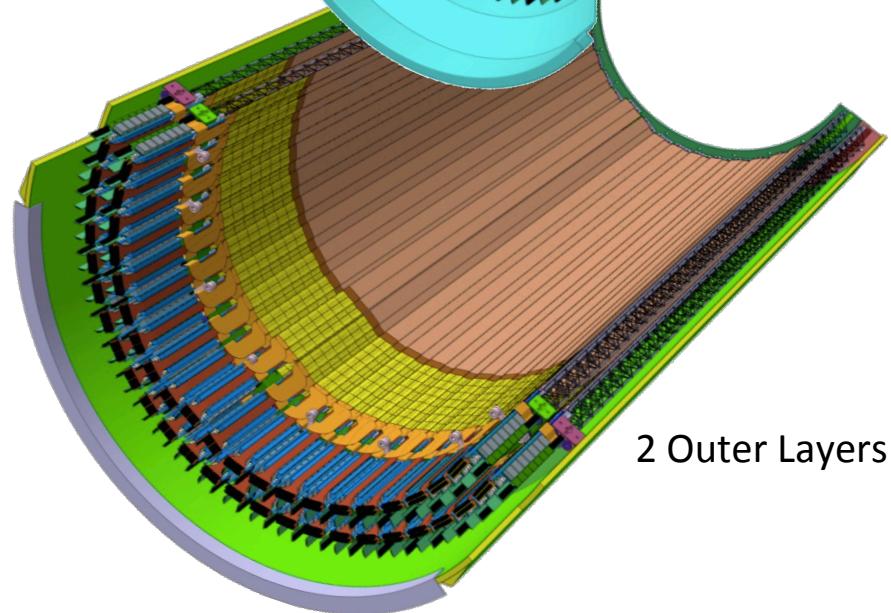
Outer Half Barrel



2 Middle Layers

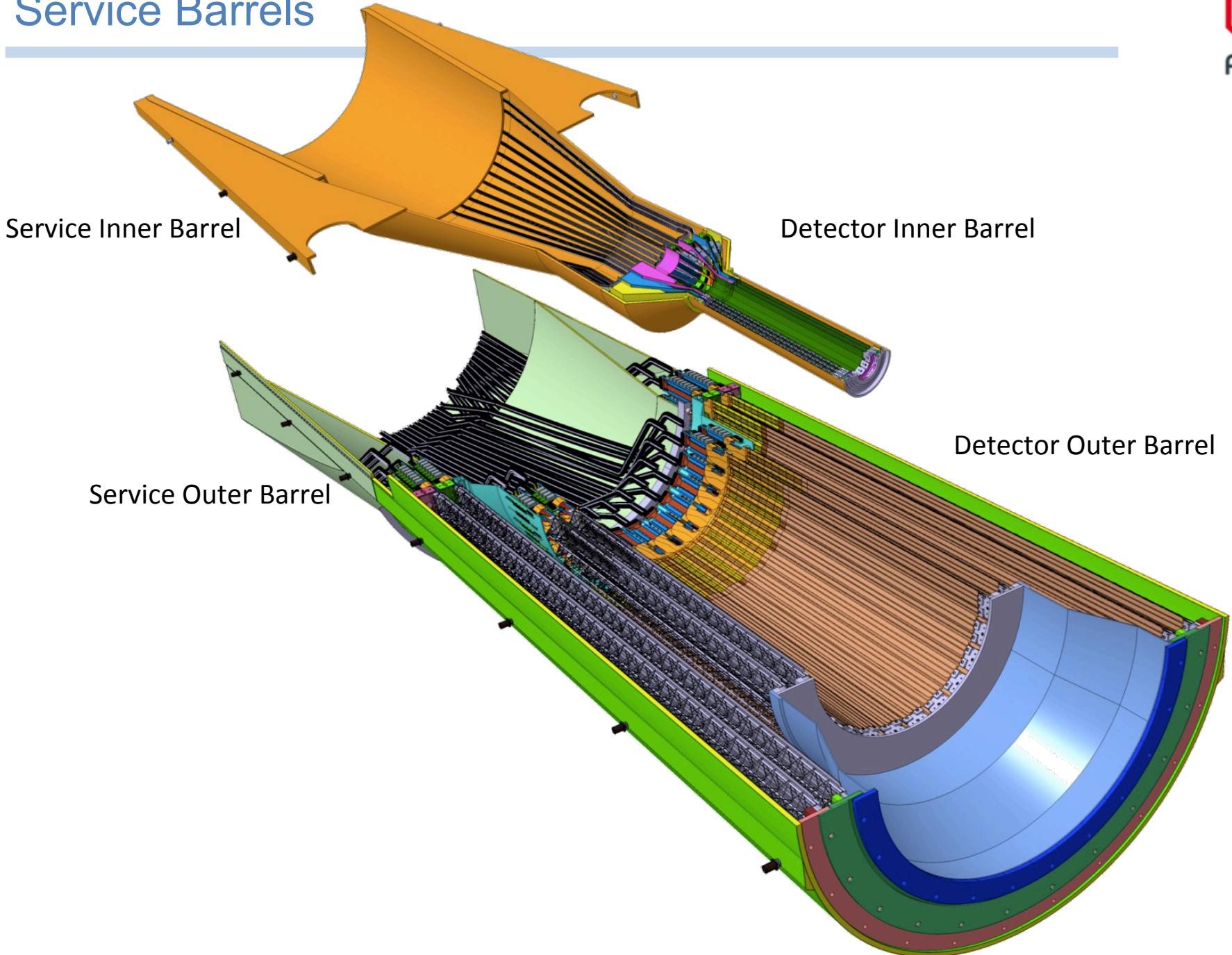


Stave



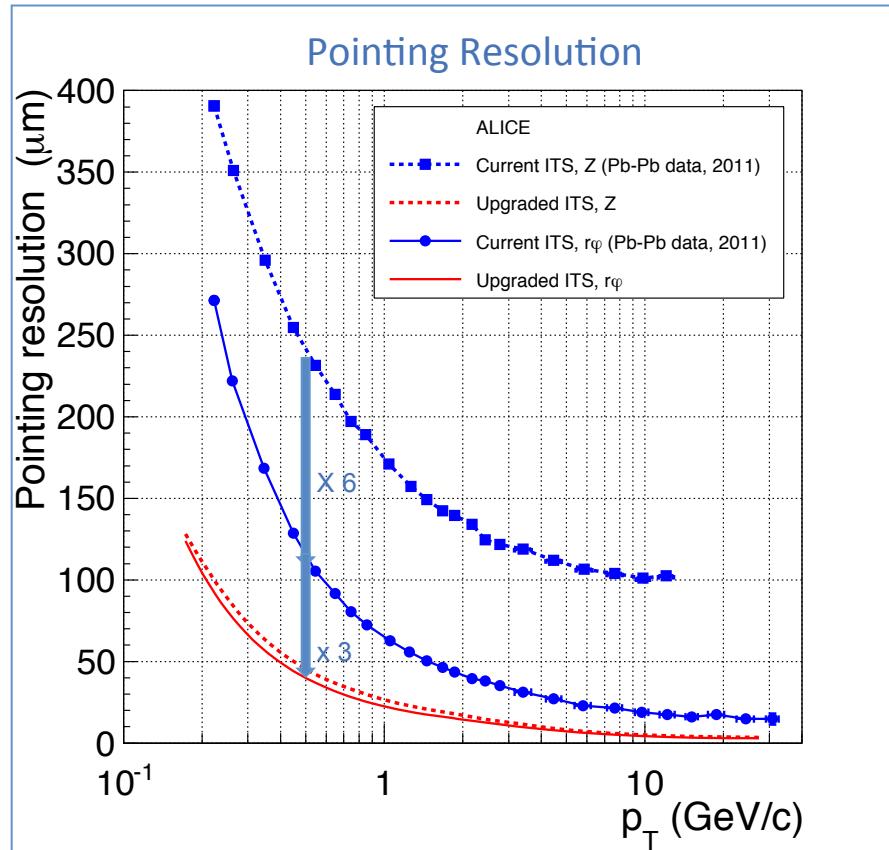
2 Outer Layers

Service Barrels

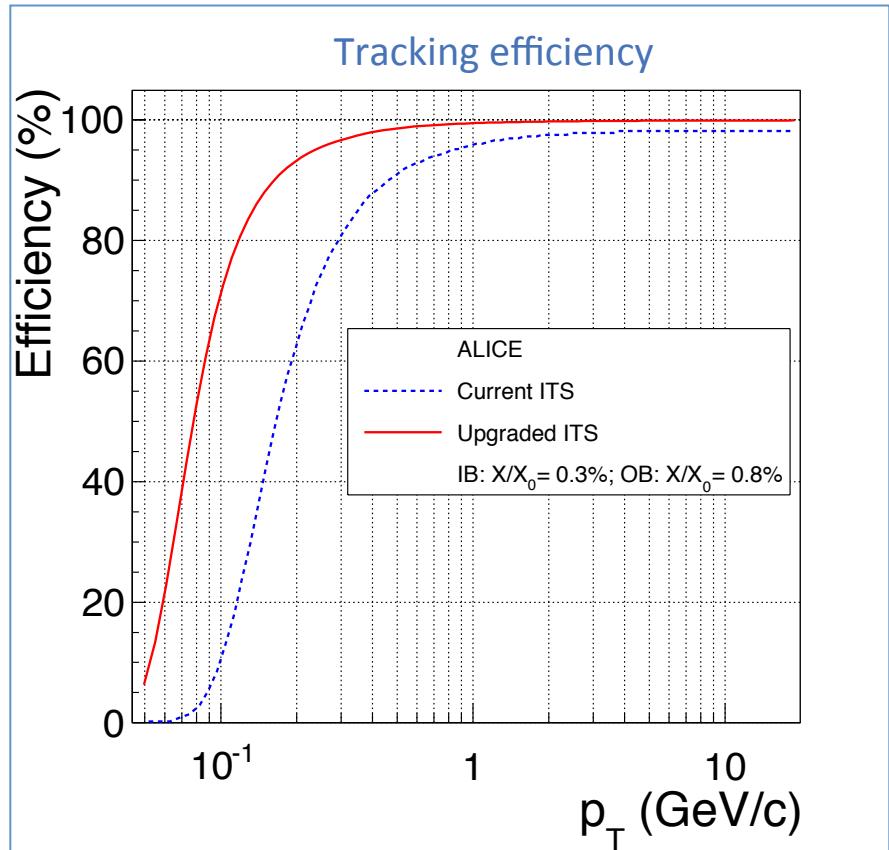


Performance of new ITS (MC simulations)

Impact parameter resolution

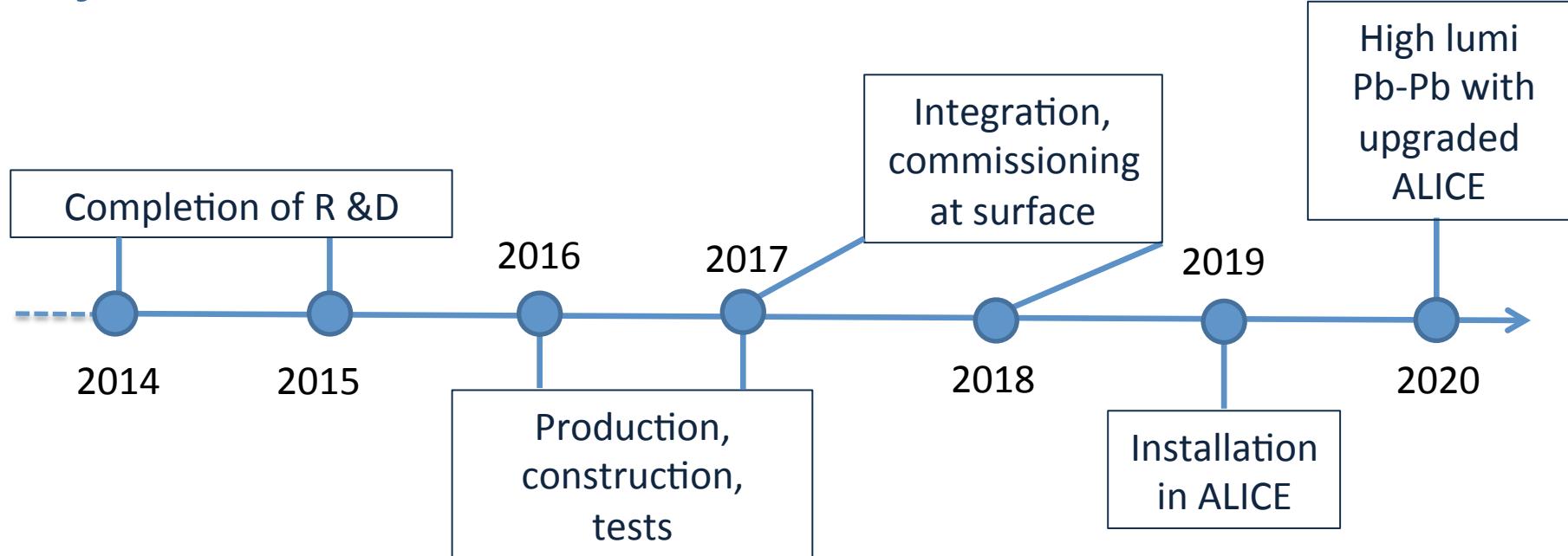


Tracking efficiency (ITS standalone)



$\sim 40 \mu\text{m}$ at $p_T = 500 \text{ MeV}/c$

Project Timeline and Collaboration



ALICE ITS Collaboration

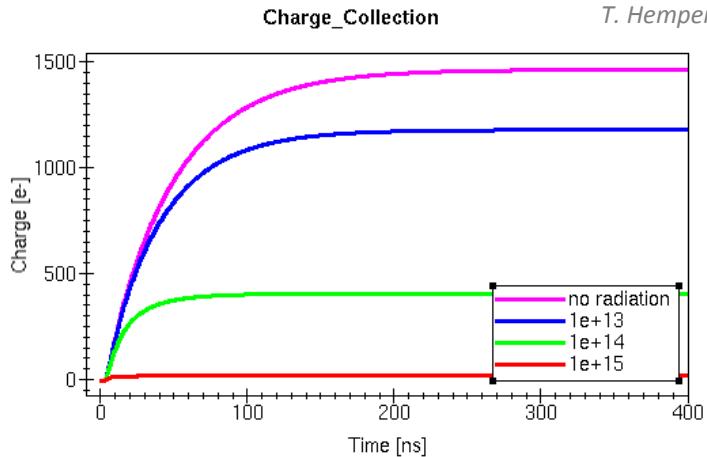
[CERN](#), [China \(Wuhan\)](#), [Check Republic \(Prague\)](#), [France \(Grenoble, Strasbourg\)](#),
[Italy \(Aless., Bari, Cagliari, Catania, Frascati, Padova, Roma, Trieste, Torino\)](#),
[Indonesia \(LIPI\)](#), [Korea \(Pusan, Inha, Yonsei\)](#), [Netherlands \(Nikhef, Utrecht\)](#),
[Pakistan \(CIIT-Islamabad\)](#), [Russia \(St. Petersburg\)](#), [Slovakia \(Kosice\)](#),
[Thailand \(Suranaree, SLRI, TMEC\)](#), [UK \(Daresbury, Liverpool, RAL\)](#), [Ukraine \(Kharkov\)](#),
[USA \(Austin, Berkeley\)](#)

Institute = participated in current ITS

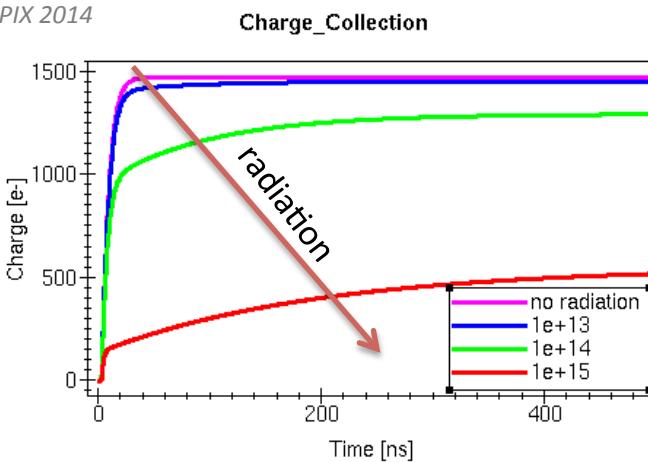
SPARES

ITS Pixel Chip – starting material

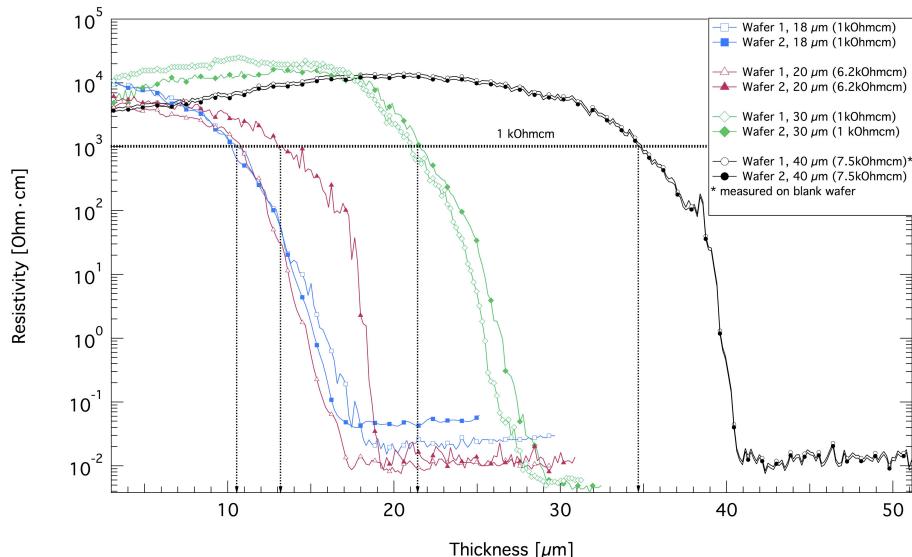
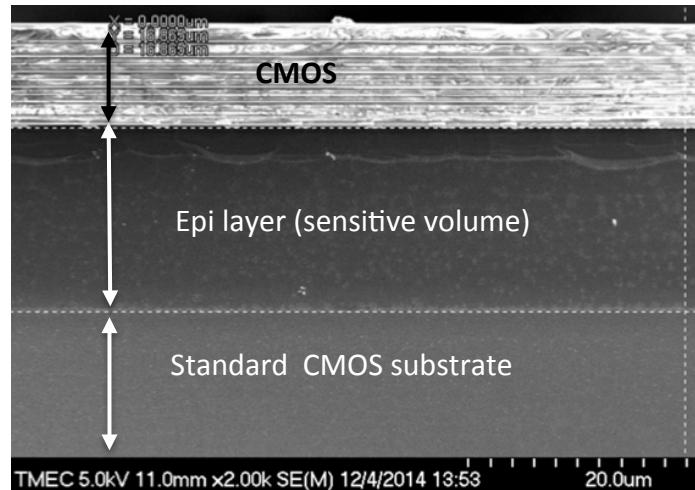
Charge collection time and recombination depend on doping concentration (Si resistivity) and radiation induced dislocations



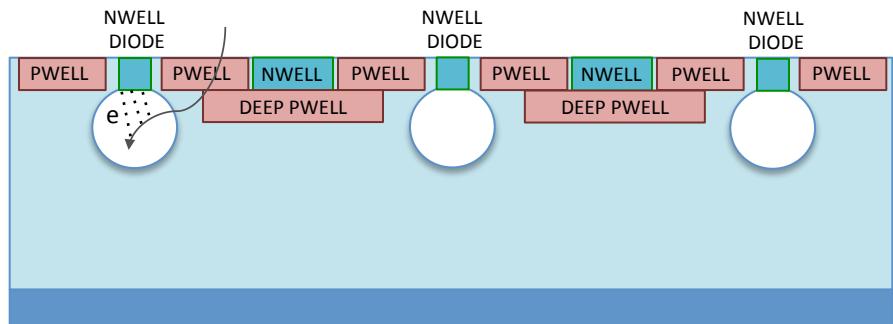
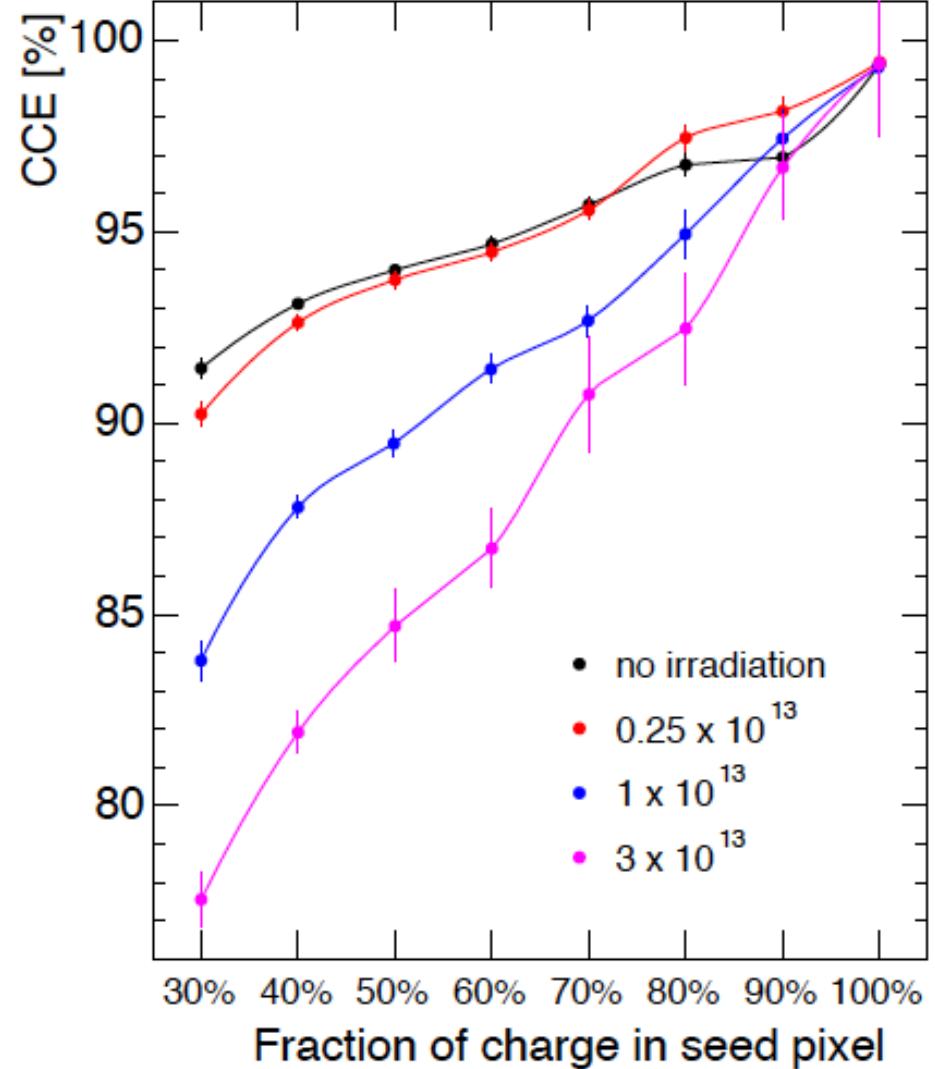
Substrate: 10 Ohm cm, NWELL: @1V PW: @ 0V



Substrate: 2k Ohm cm, NWELL: @1V PW: @ 0V

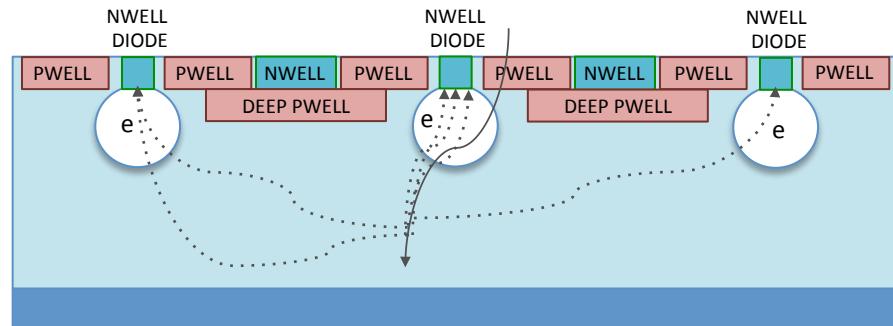


ITS Pixel Chip – charge recombination



^{55}Fe X-ray absorption close to collection diode

- small diffusion => small recombination
- Signal collected in a single pixel

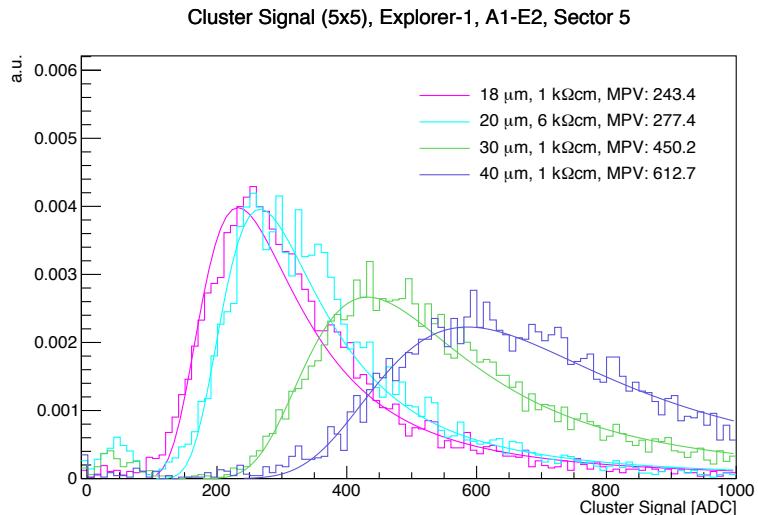


^{55}Fe X-ray absorption far from collection diode

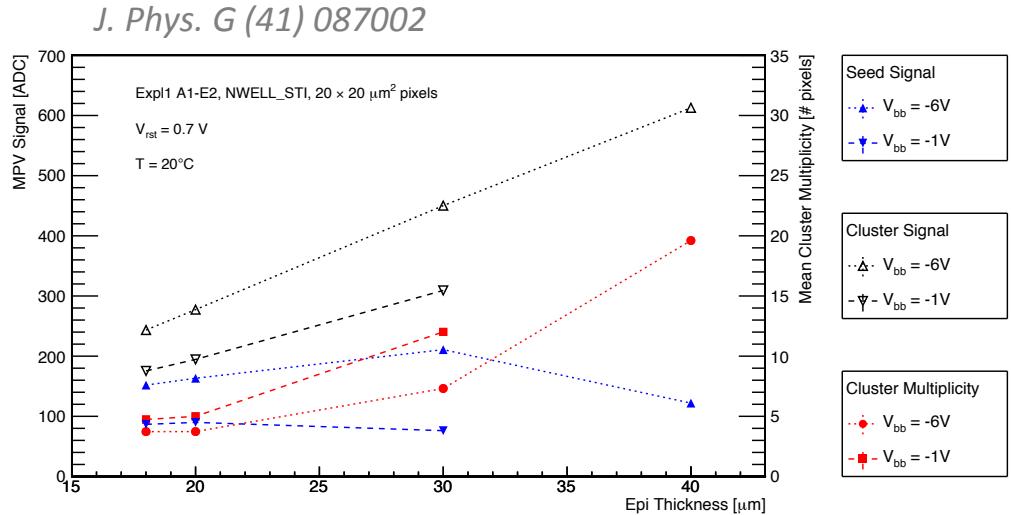
- large diffusion => large recombination
- signal spreads over several pixels

ITS Pixel Chip – starting material

Thicker epitaxial layers will yield more charge but ... diffusion increases cluster size



J. Van Hoorne, TIPP2014



Measurements done at Desy test beam with 3.2 Gev/c positrons

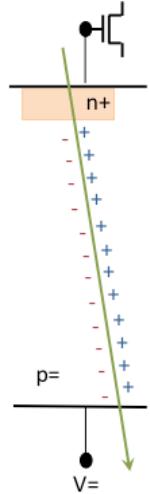
- Cluster charge increases linearly with epi-layer thickness
- Cluster size increases with epi-layer thickness

optimum epi thickness (maximum seed signal) increases by increasing depletion volume

ITS Pixel Chip – starting material

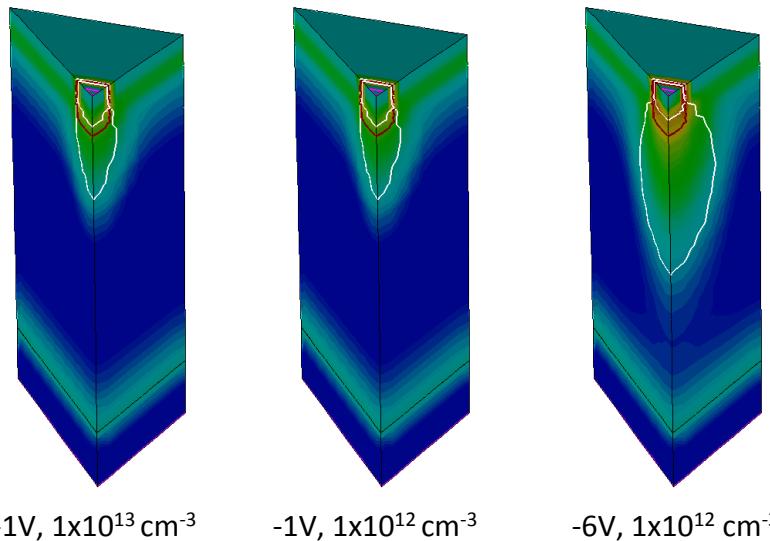
Low input capacitance decisive to achieve large S/N at low power

(W. Snoeys, NIMA 731 (2013) 125-130)



NWELL DIODE output signal = Q / C

- Minimize spread of charge over many pixels
- minimize capacitance:
 - ➡ small diode surface
 - ➡ large depletion volume

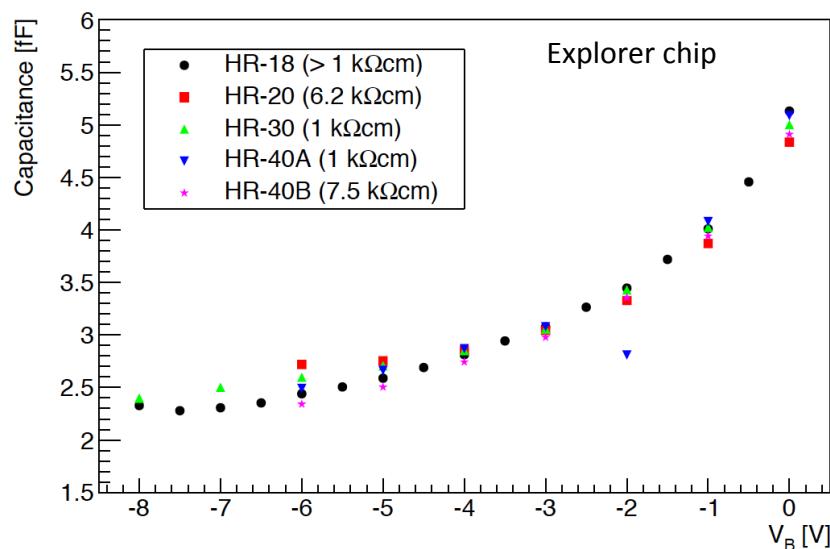


-1V, $1 \times 10^{13} \text{ cm}^{-3}$

-1V, $1 \times 10^{12} \text{ cm}^{-3}$

-6V, $1 \times 10^{12} \text{ cm}^{-3}$

Diode $3\mu\text{m} \times 3\mu\text{m}$ square n-well , White line: boundaries of depletion region



- ☞ Pixel input capacitance decreases with increasing reverse bias, in agreement with simulated size of depletion region
- ☞ Minor influence of epi resistivity for current pixel layout

Pixel chip – interconnection to flex PCB

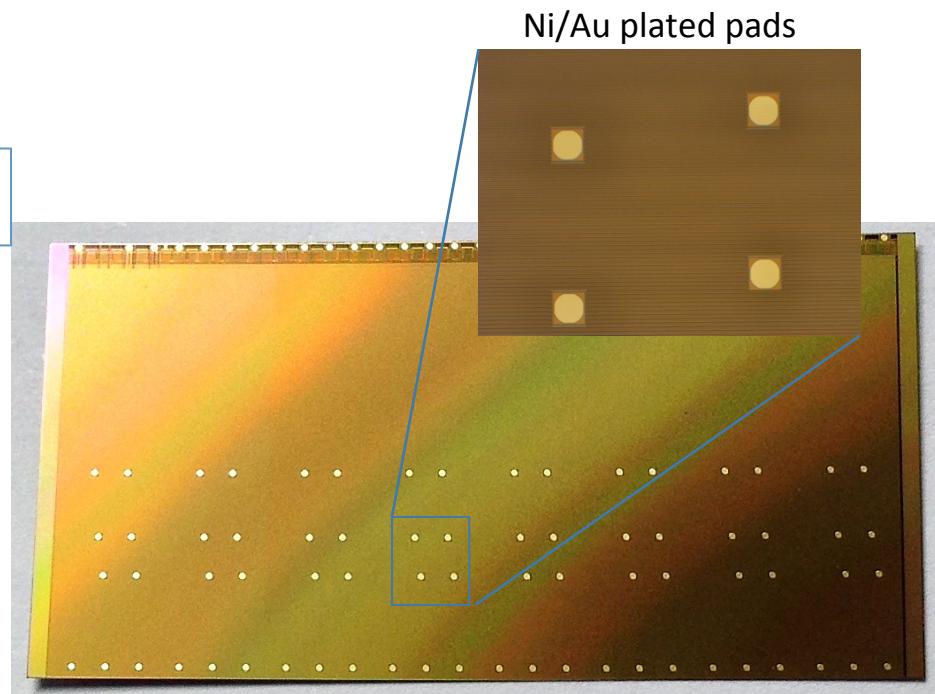
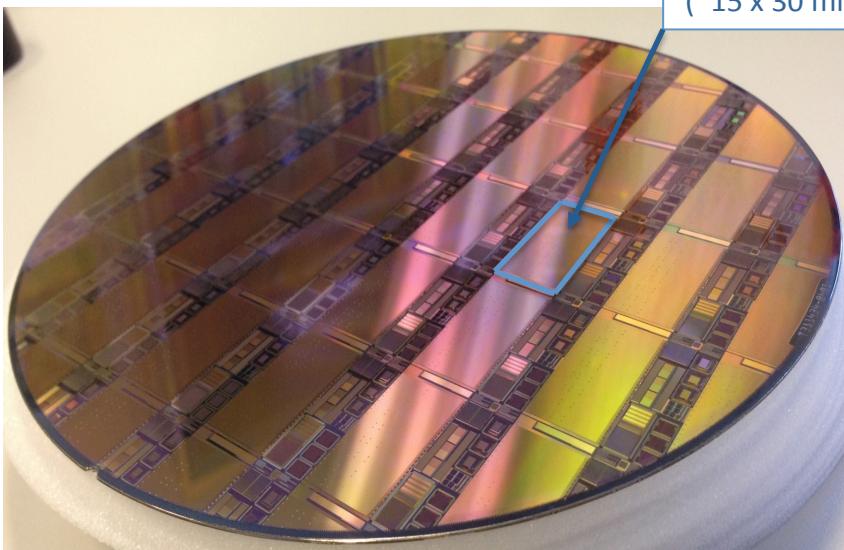
Solder Pads

- to solder the chip on the FPC, Al pads need Ni-Au plating (wet-able surface)
- plating is done on wafer using electroless Ni-Au plating, prior to thinning and dicing
- R&D experience 2012-now: plating of about 50 wafers (pad wafers and CMOS wafers)

Status

Market survey concluded

Tendering starting soon



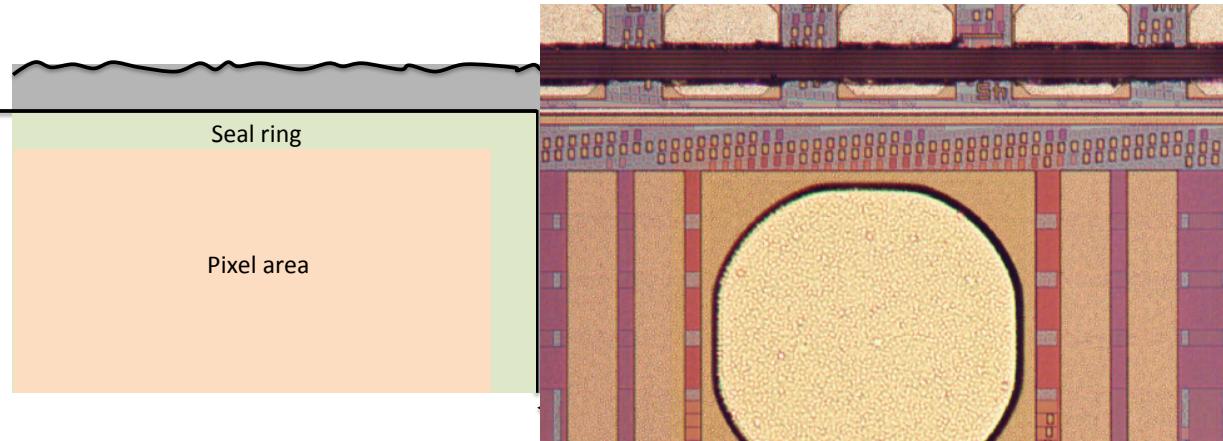
Contact pads are distributed over the matrix
(custom designed)

Pixel chip - thinning & dicing

- Diamond wheel pre-dice before grind (DBG) → extended experience (all types of wafers) with **Rockwood** (France)
- **Main challenge:** picking of large dies after dicing and grinding (**50µm thick chip**)
→ Development of special tools/procedures

Requirements

- Max. extension from the sealring:
25 µm
- Chipout/cracks contained within
25 µm extension region
- No cracks or chip outs touch the
seal ring
- Thickness variation: $(50 \pm < 5)$ um



Experience (DBG) with blanks, pad wafers and fully processed CMOS wafers

Experience to handle **large dies** (pALPIDEfs)

✓ 90 wafers diced and thinned to 50 µm

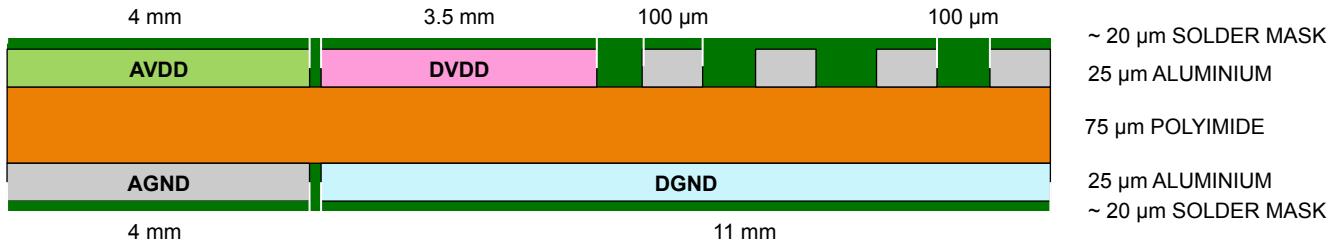
Status

Market survey in preparation, will be followed by tender in late summer 2015

Inner Barrel Stave – flexible printed circuit

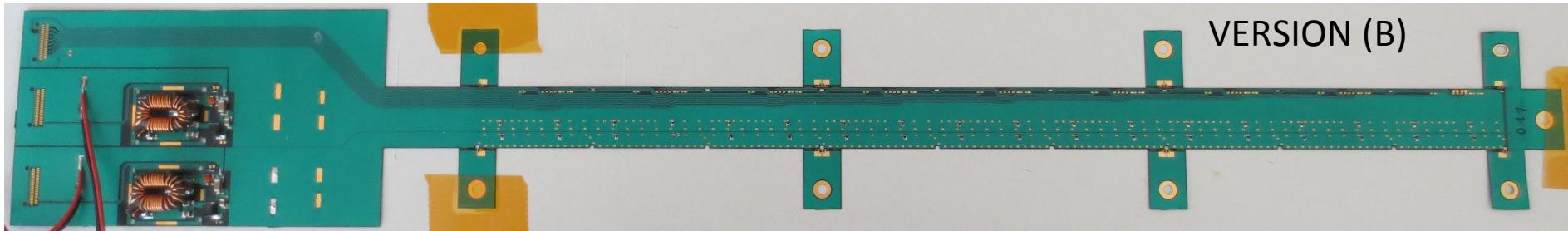
IB Flexible Printed Circuit prototypes (Al power planes and signal tracks)

Metallised vias of
220 μ m diameter



Status

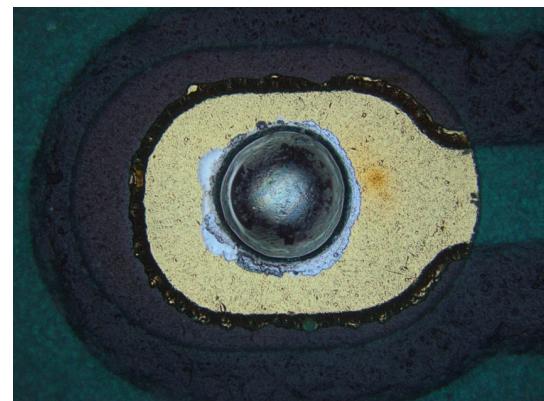
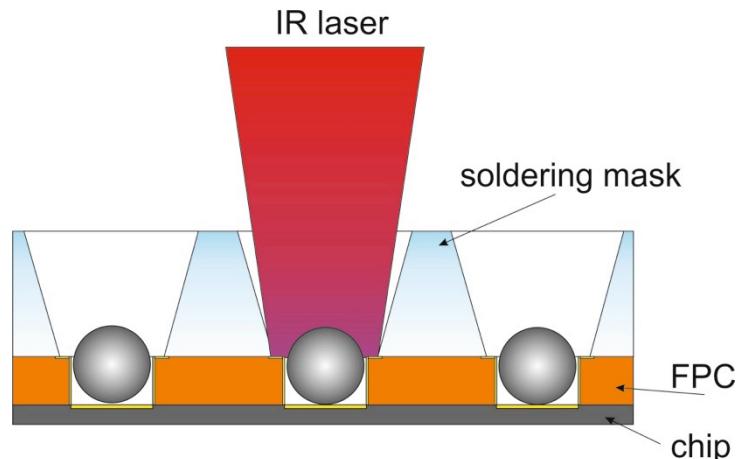
Two FPC versions (differ for the location of DC-DC converters)
ready to be tested with ALPIDE-2



Interconnection of pixel chip to flex PCB

Laser Soldering

- Flux-less soldering of 200 µm diameter Sn/Ag(96.5/3.5) balls (227 °C melting T) in vacuum ($\leq 10^{-1}$ mbar)
- IR diode laser, 976 nm, 25 W, 50 mm focal length, 250 µm beam spot size
- Laser power modulated by pyrometer, programmable T profile ensures precise limitation of heating
- Soldering mask (in Macor® or Rubalit ®) used to press FPC on chip and guide soldering balls inside FPC vias
- Solder provides electrical and mechanical connection → no glue



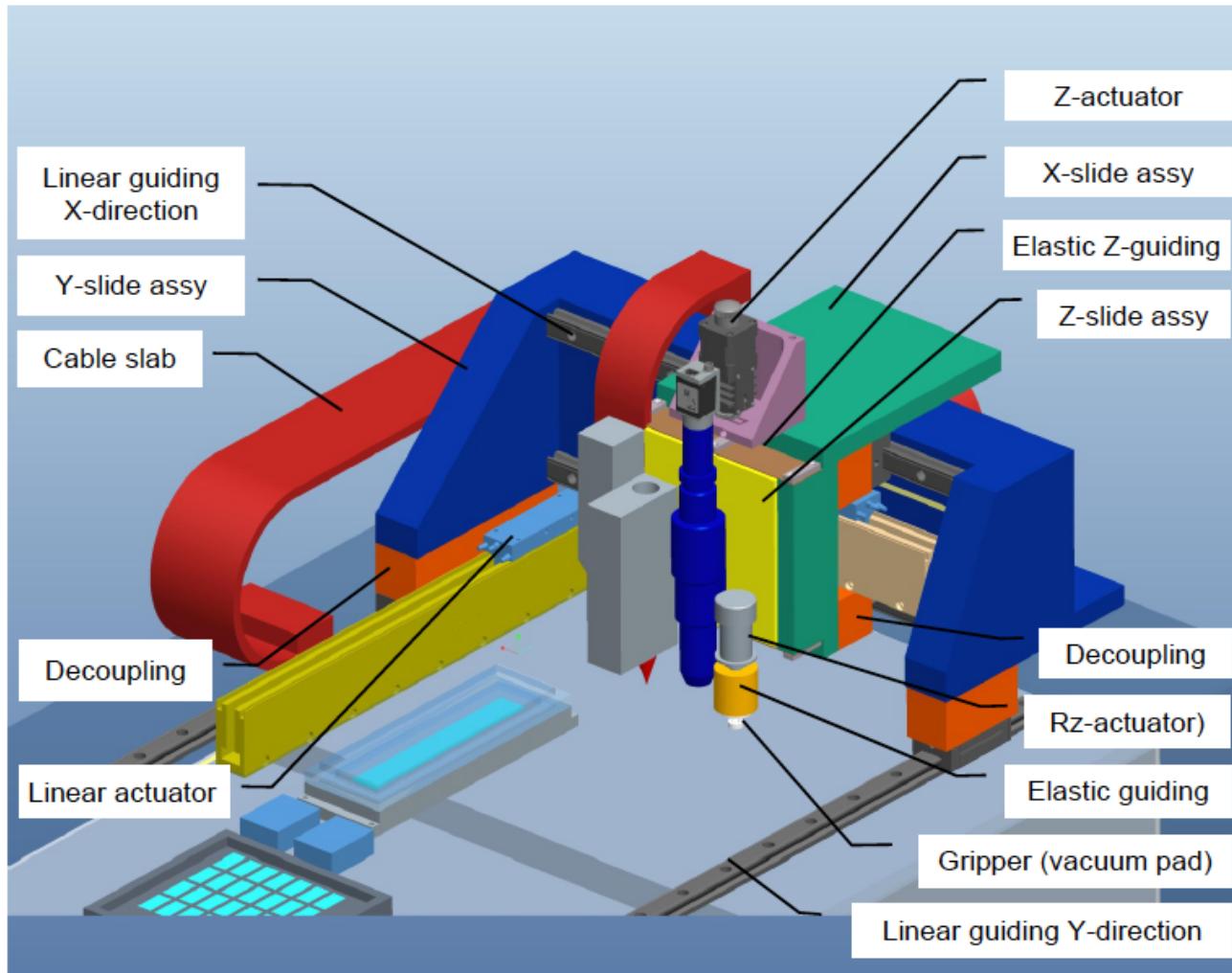
Module Assembly Machine

IB and OB module assembly

- Semi-automatic procedure
- custom machine (specialized company)

Status

- Contract adjudicated to IBS (NL)
- Delivery of first prototype October 15



6 Machines

Inner Barrel & MFT

- CERN

Outer Barrel

- Bari
- Strasbourg
- Liverpool
- Pusan
- Wuhan

Same machines used also for chip testing

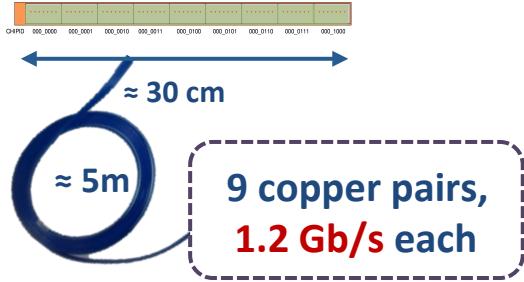
- CERN
- Pusan

Independent machine for chip testing

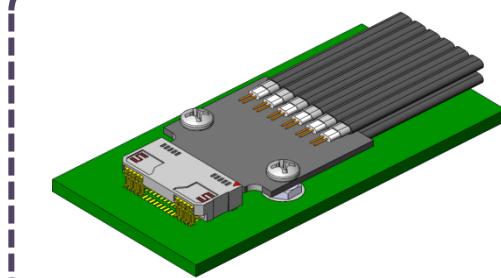
- Yonsei (Seoul)

Readout Unit – system overview

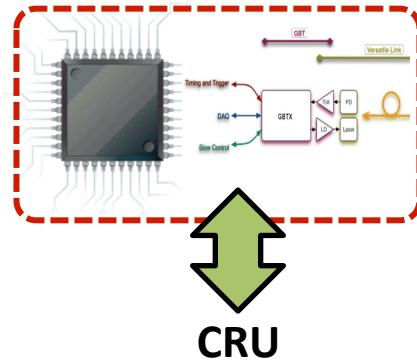
Inner layers (0, 1, 2) staves:
9 masters for each stave



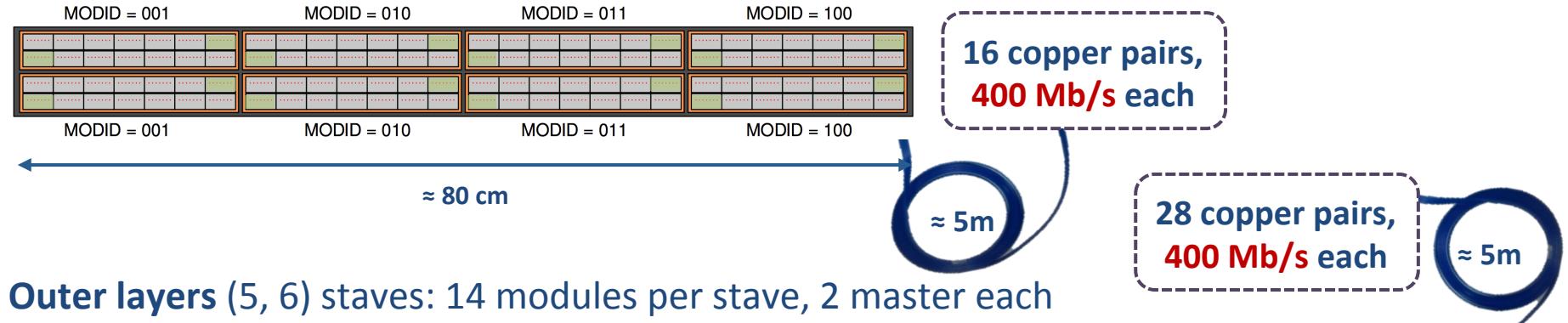
12 pairs Twinax copper assembly



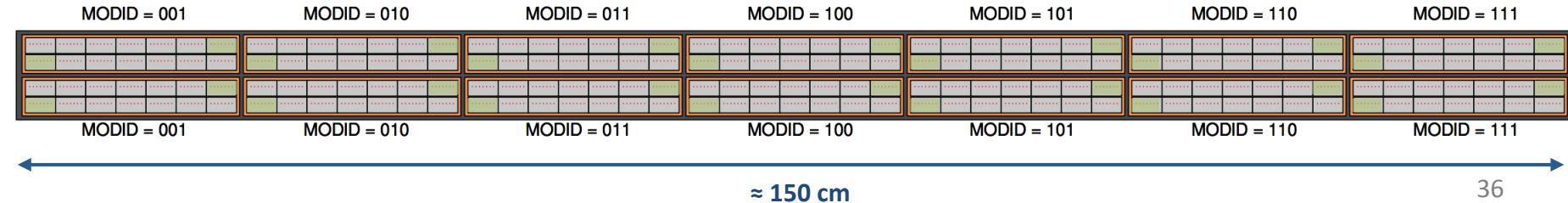
Readout Unit



Mid layers (3, 4) staves: 8 modules per stave, 2 master each



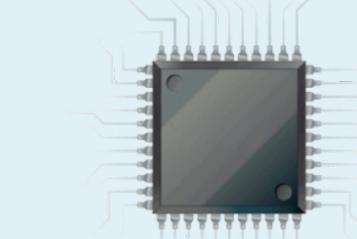
Outer layers (5, 6) staves: 14 modules per stave, 2 master each



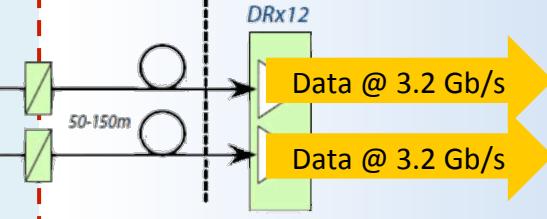
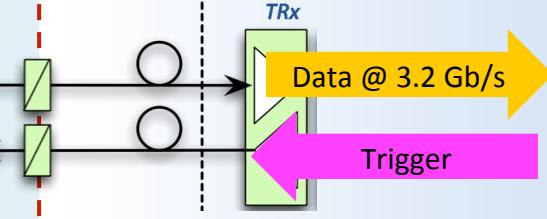
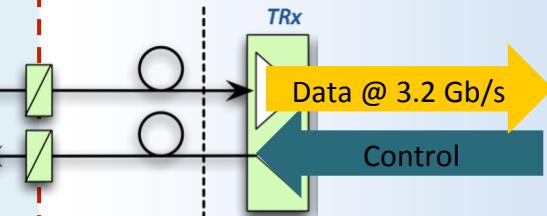
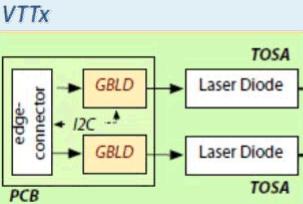
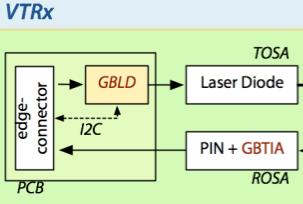
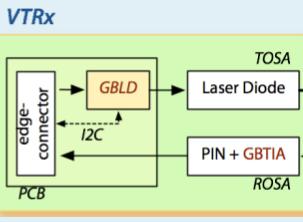
Readout – single modular Readout Unit for all layers

Inner Layers

Readout Unit



**2 × 16 channel FPGA
per half stave (only
one used for inner
layers)**



Mid & Outer Layers

Power Unit



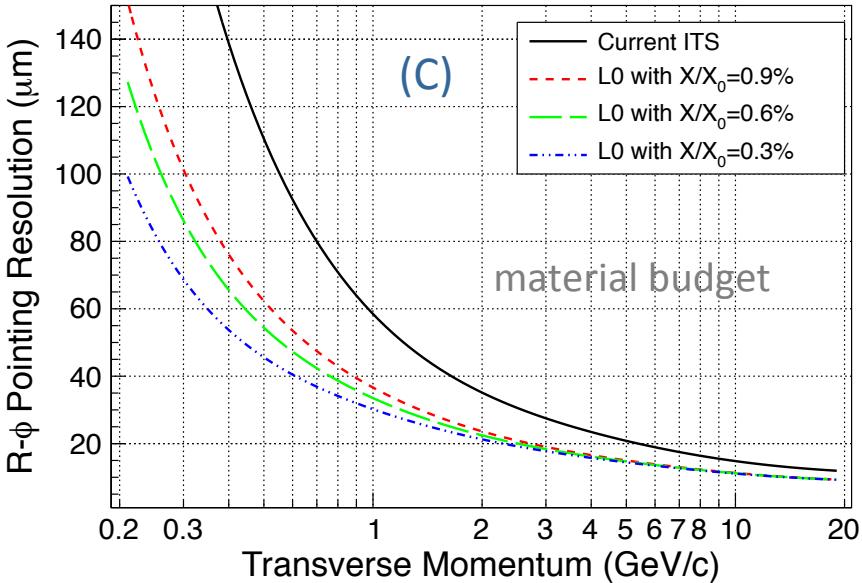
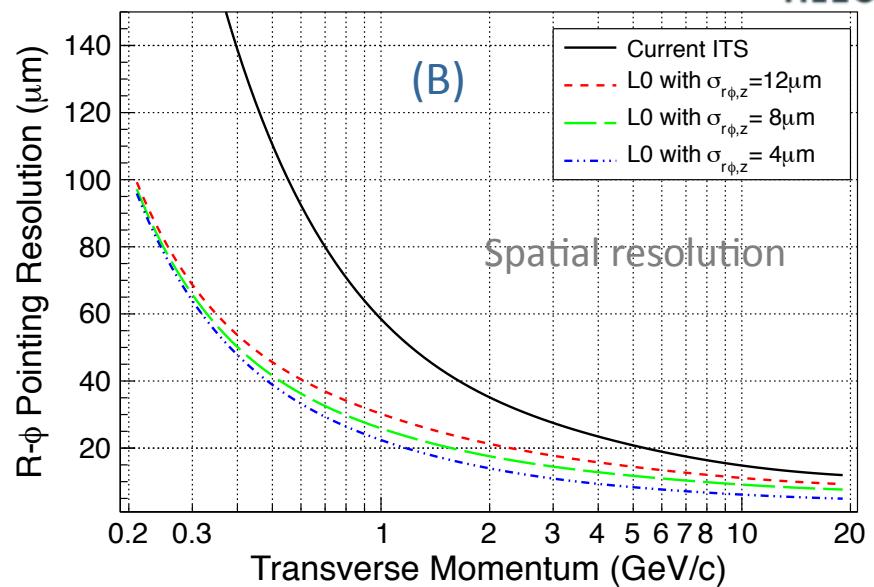
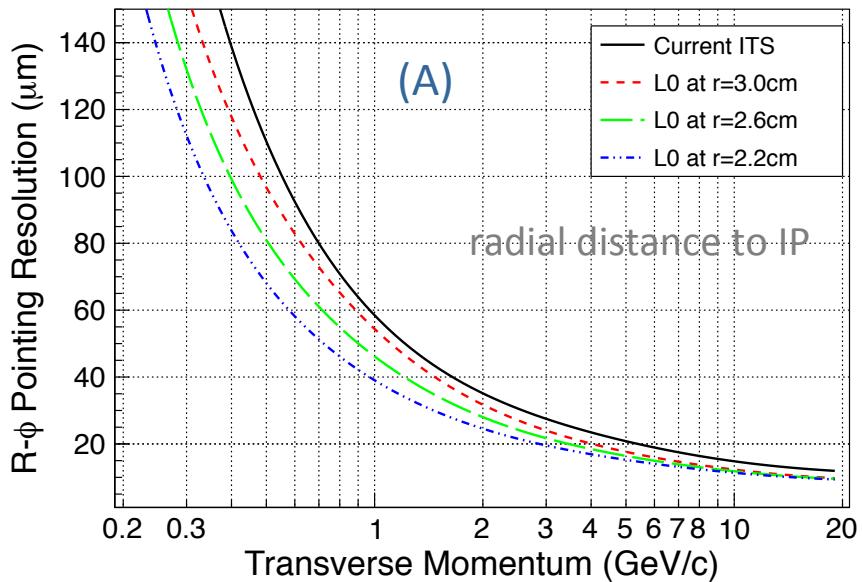
Control

Not mandatory for
“baseline” (Pb-Pb @ 50 kHz)
operations.

Independent to control system

Cables from power supply

Impact parameter studies (ALICE ITS Upgrade)



- Current ALICE ITS
 - ◊ radial position of first layer: 39mm
 - ◊ x/X_0 : 1.14% per layer
 - ◊ spatial resolution (r-phi): 12 μm
- A) current ITS + L0: $x/X_0 = 0.3\%$, res.=4 μm ;
- B) current ITS + L0: $r = 22\text{mm}$, $x/X_0 = 0.3\%$;
- C) current ITS + L0: $r = 22\text{mm}$, $x/X_0 = 0.3\%$;